

National Synchrotron Light Source II



Current Status of Developing Ultrafast Mega-electron-volt Electron Microscope

Xi Yang

on behalf of BNL UEM team

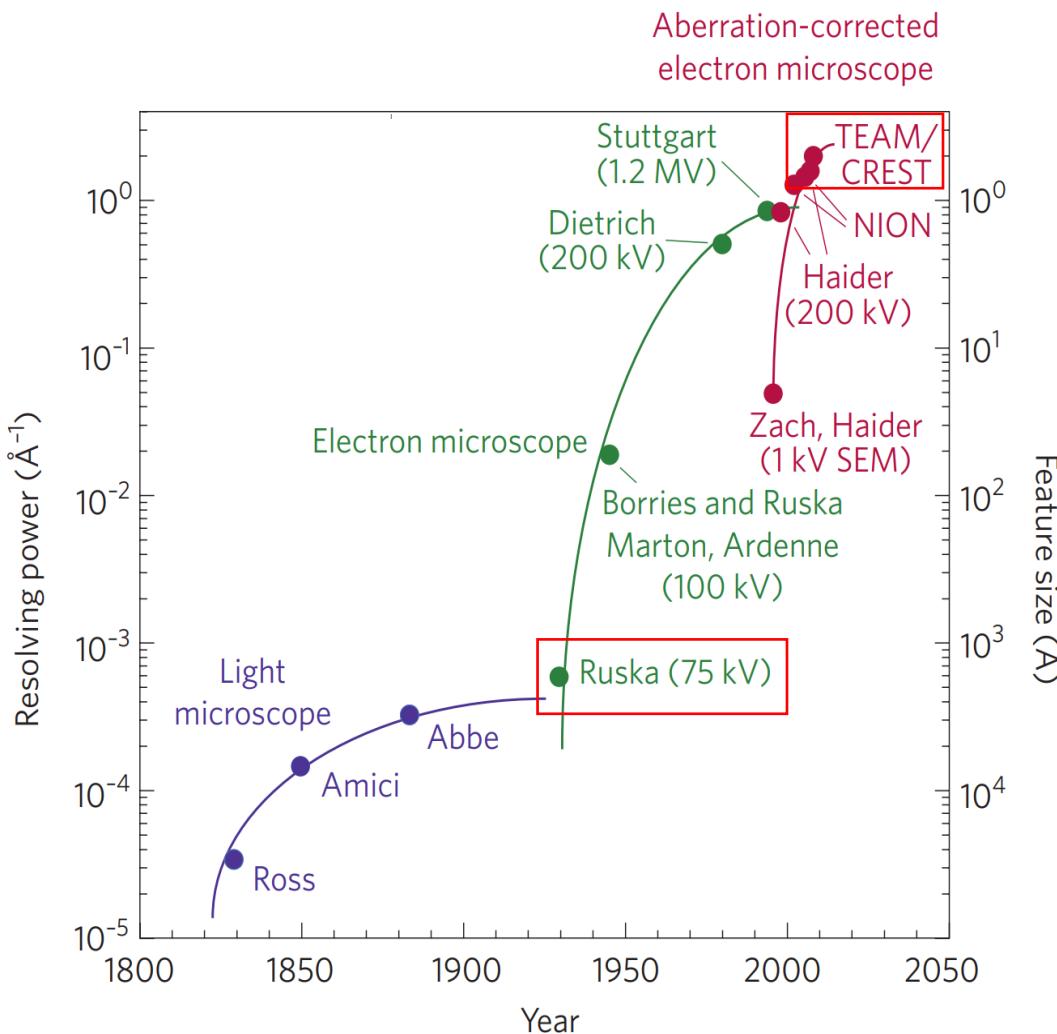
08/10/2022



- **Introduction**
 - Review of scientific case for conventional TEM
 - Promise of MeV-microscopy
- **History of MeV microscopy**
- **Review of the state-of art in the MeV-UEM field**
- **Physics & engineering challenges & solutions in reaching nm resolution**
 1. Energy jitter
 2. Interaction of MeV-electrons to sample
 3. Mechanical stability
 4. Detector
- **Conclusion**

Transmission electron microscopy

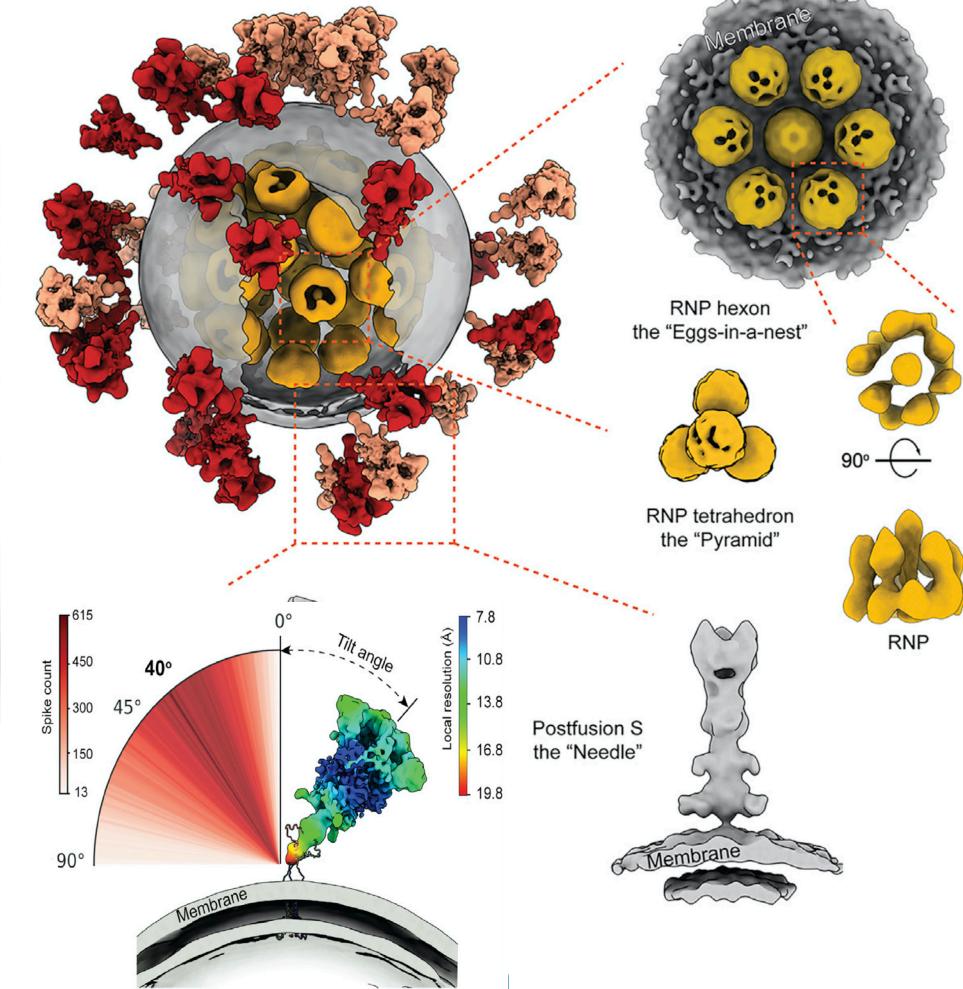
- Imaging tool for material science, chemistry, physics, biology, and industry
- Atomic resolution with aberration correction



Cryo-TEM



An intact virus to fight against covid-19

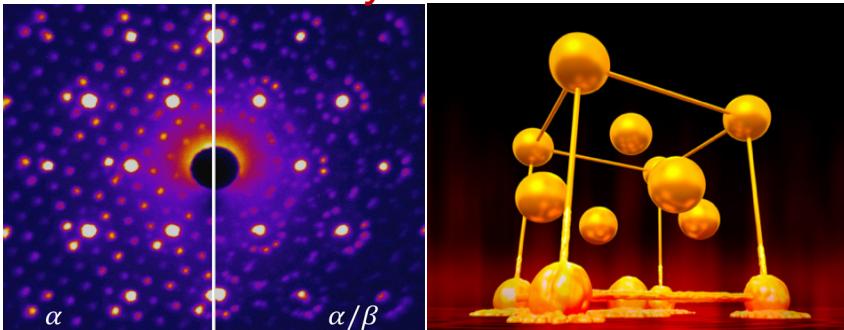


D. A. Muller, *Nat. Mater.* 8, 263 (2009)
Adapted from H. H. Rose (2009)

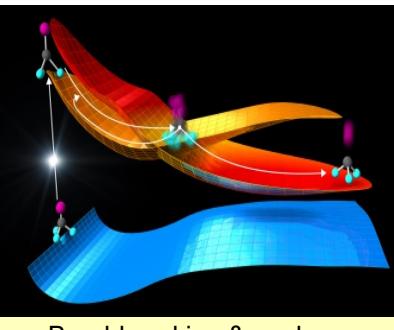
Yao, H. et al. *Cell* 183, 730 (2020)

Ultrafast science enabled by MeV UED

Courtesy of Xiaozhe Shen

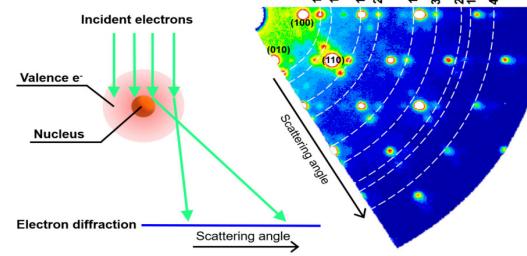


Phase switch with a single flash of light (*Sci. Adv.* 4, eaau5501 (2018)).

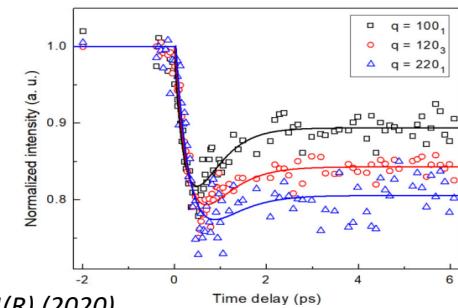


Bond-breaking & nuclear wavepacket passing through conical intersections (*Science* 361 64–67 (2018))

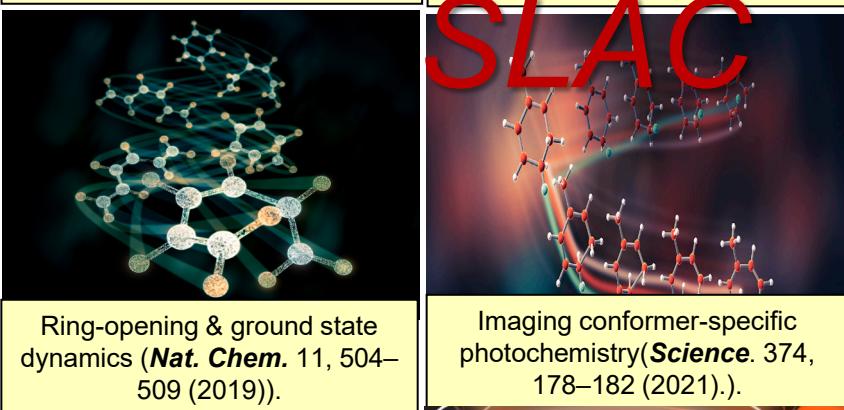
Concurrent probing electron-lattice dephasing (BNL)



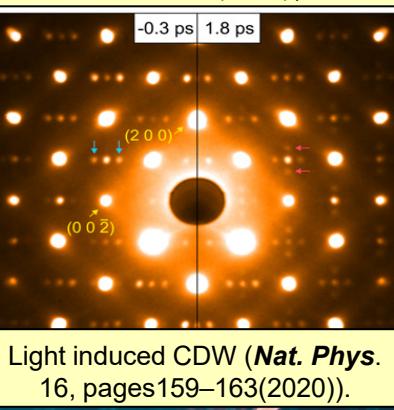
Li et al., Phys. Rev. B 101, 100304(R) (2020)



High repetition rate electron scattering beamline (HiRES) LBNL

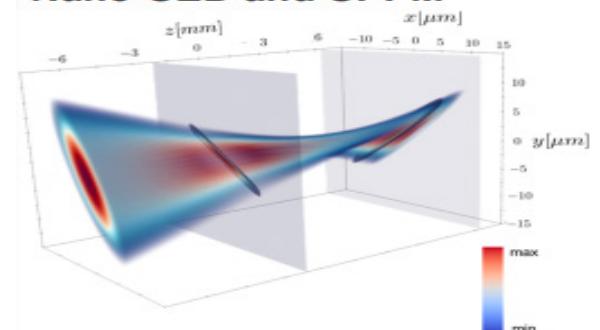


Ring-opening & ground state dynamics (*Nat. Chem.* 11, 504–509 (2019)).

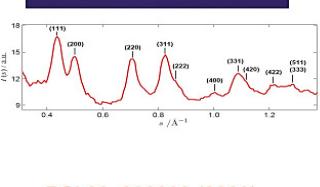
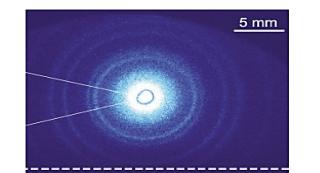


Light induced CDW (*Nat. Phys.* 16, pages 159–163 (2020)).

Nano-UED and UPPM

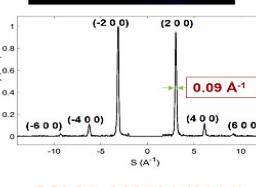
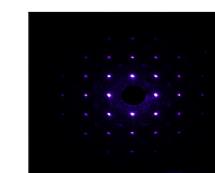


THU, 2009



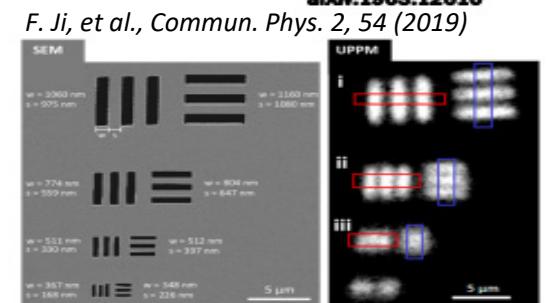
RSI 80, 083303 (2009)

SJTU, 2014

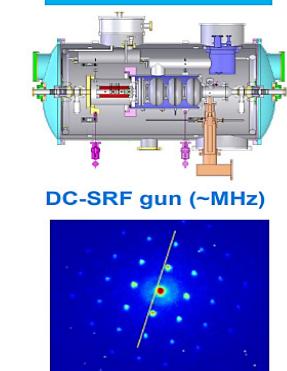


RSI 85, 083701 (2014)

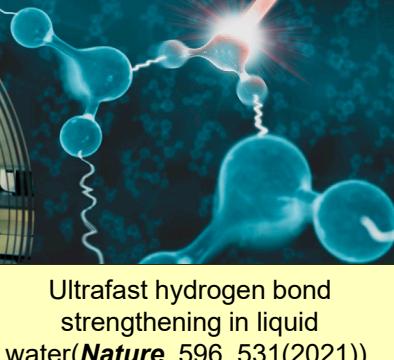
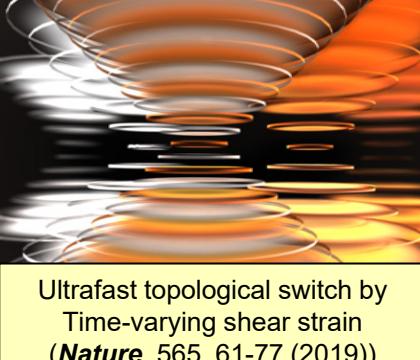
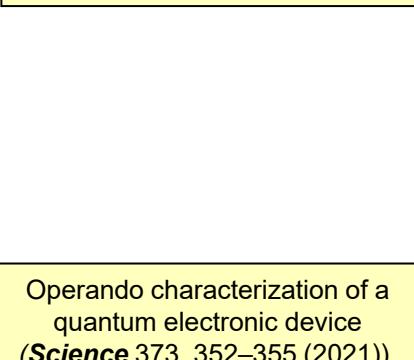
arXiv:1901.03443
arXiv:1903.12610



PKU, 2015



APL 107, 224101 (2015)



Operando characterization of a quantum electronic device (*Science* 373, 352–355 (2021)).

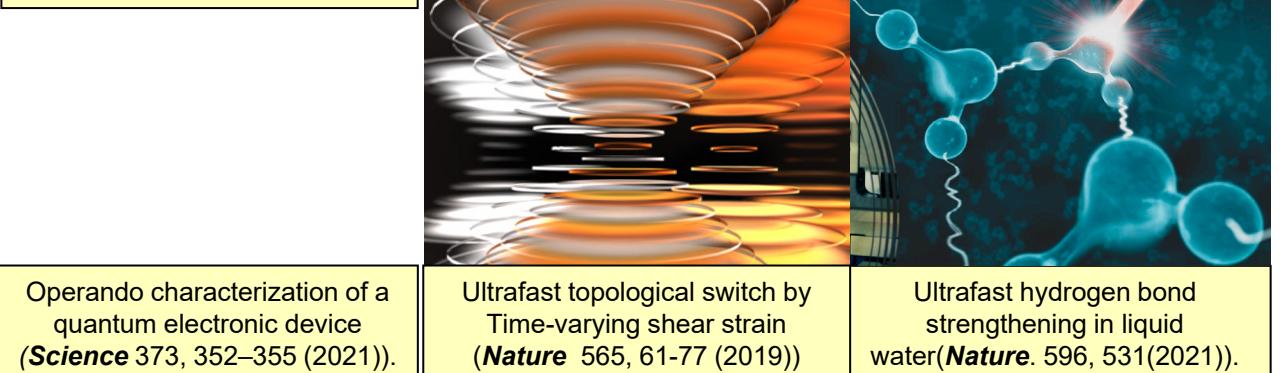
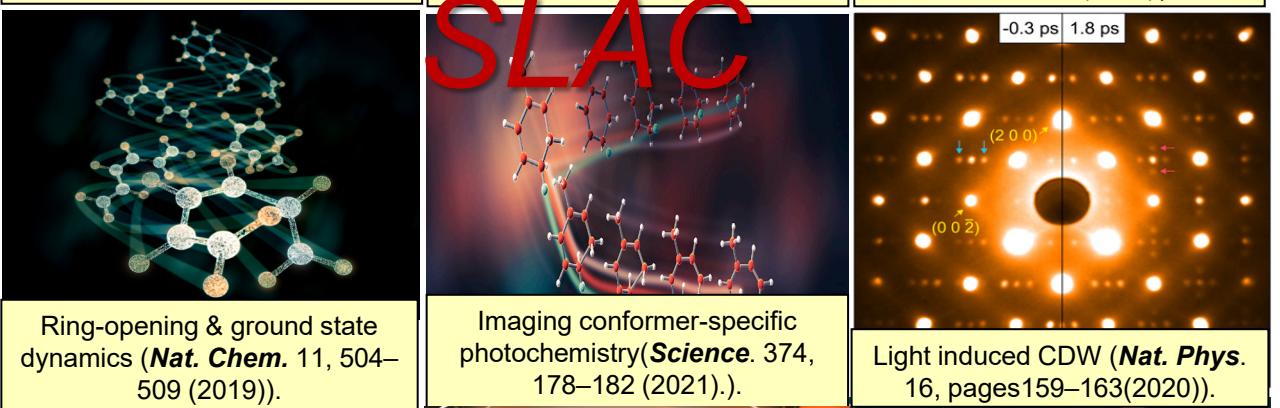
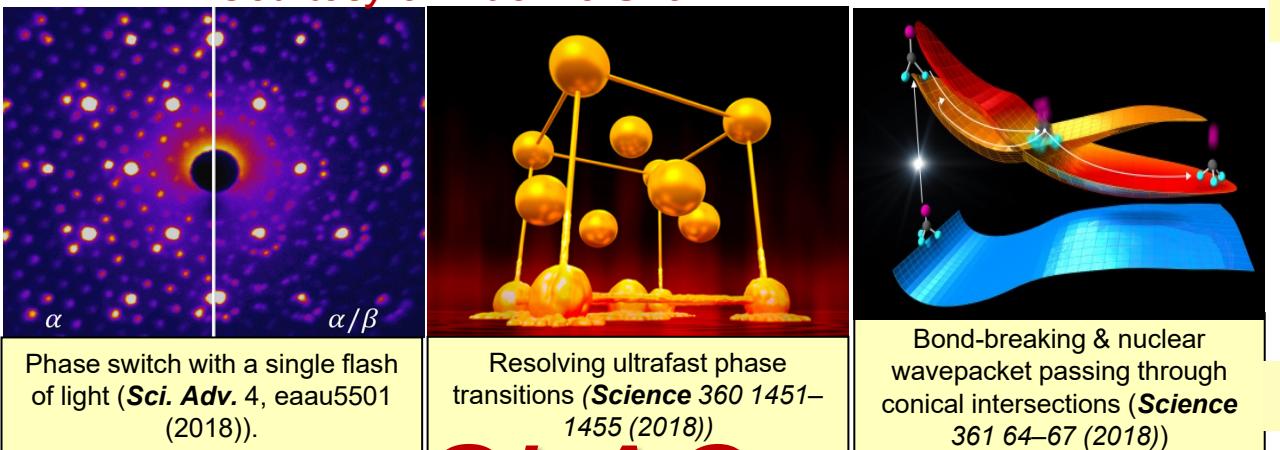
Ultrafast topological switch by Time-varying shear strain (*Nature* 565, 61–77 (2019))

Ultrafast hydrogen bond strengthening in liquid water (*Nature* 596, 531 (2021)).

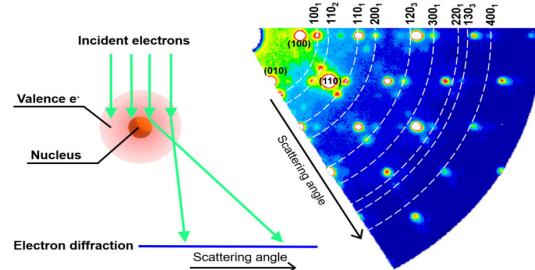
Ultrafast science enabled by MeV UED

Toward real space imaging enabled by MeV Microscopy

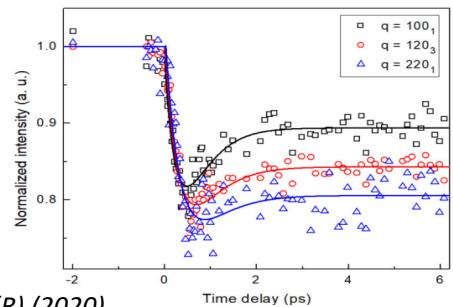
Courtesy of Xiaozhe Shen



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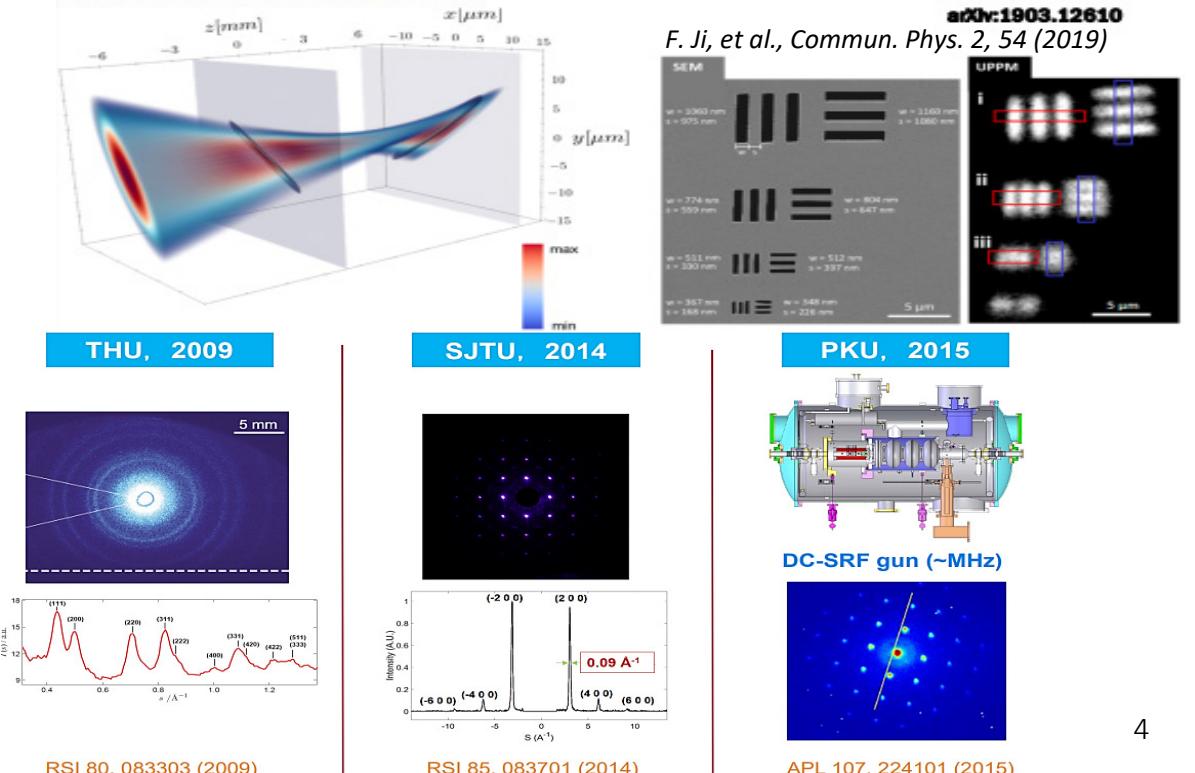


Li et al., Phys. Rev. B 101, 100304(R) (2020)



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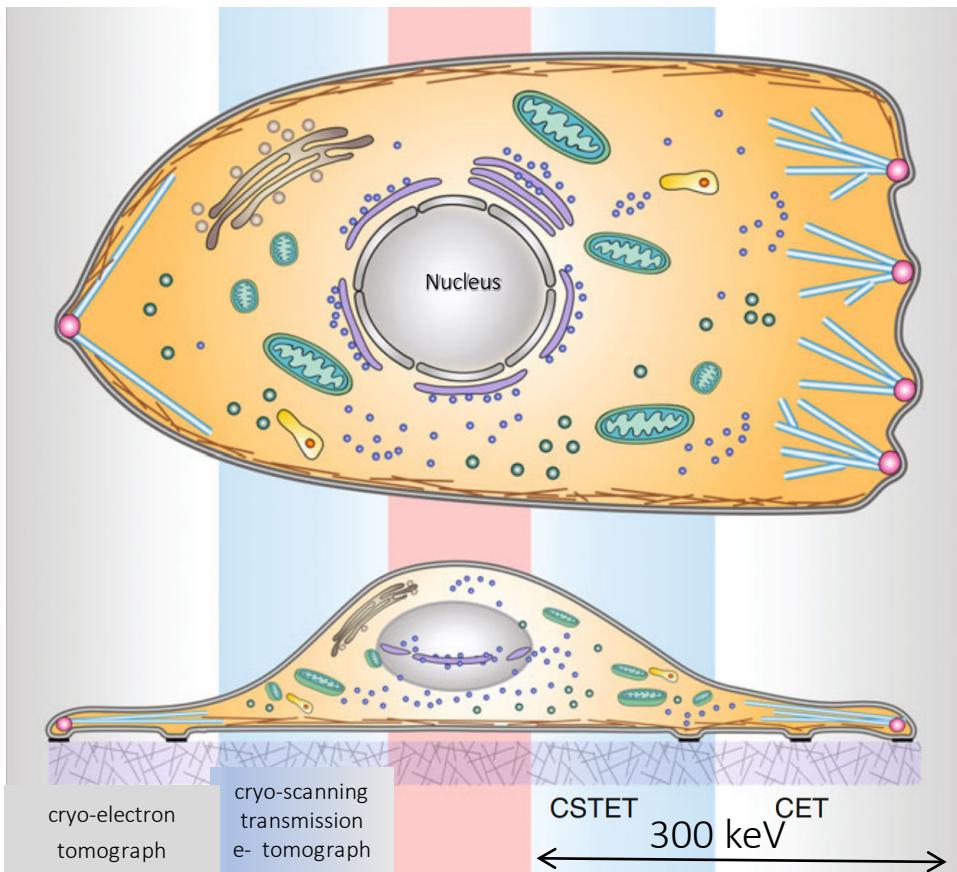


Promise of MeV Microscopy

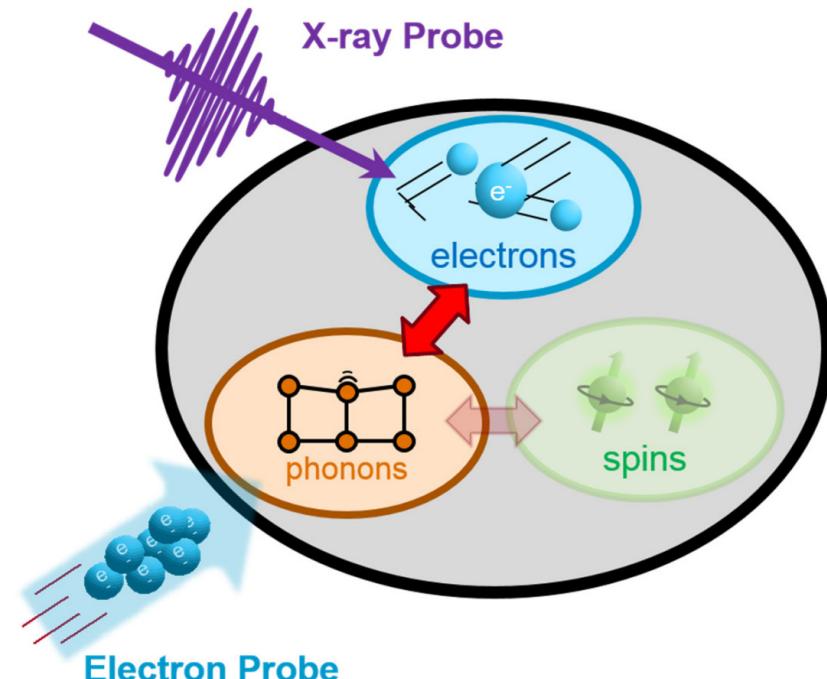
Two different types of applications

- **Life science application:** 3D-image thick bio-samples
- No need of cryo-FIB (focused ion beam) to slice thick cells
- Limited by 5-10 lamellae/day, “blindly” select target
- Speed up discovery

- Probe into ultrasmall and ultrafast world
- Real-time visualize structural dynamics in real space
- Allow direct probing of charge-spin-lattice interactions



S.G. Wolf, et al., *Cellular Imaging*, Springer



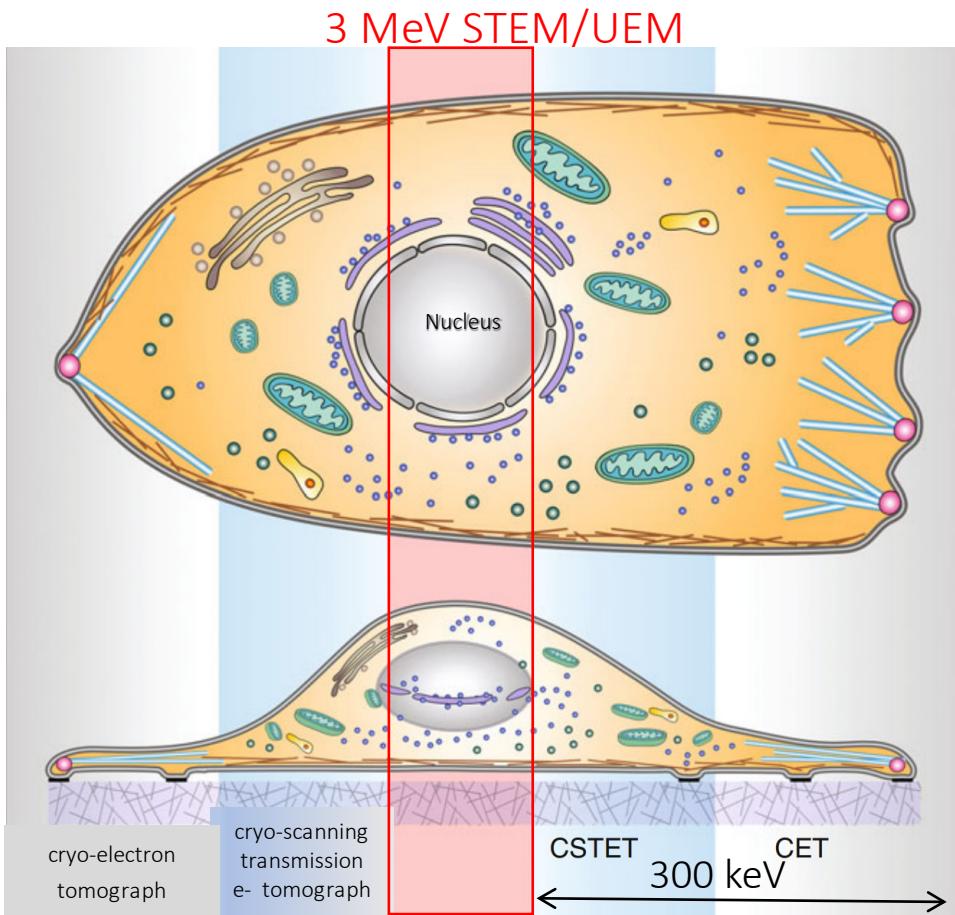
R.K. Li, et al., IBIC 2019

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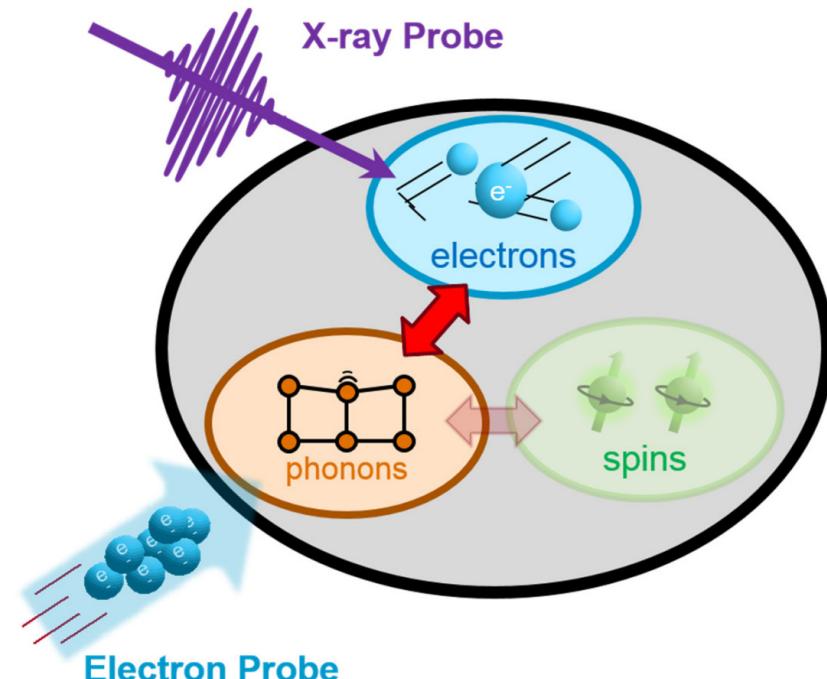
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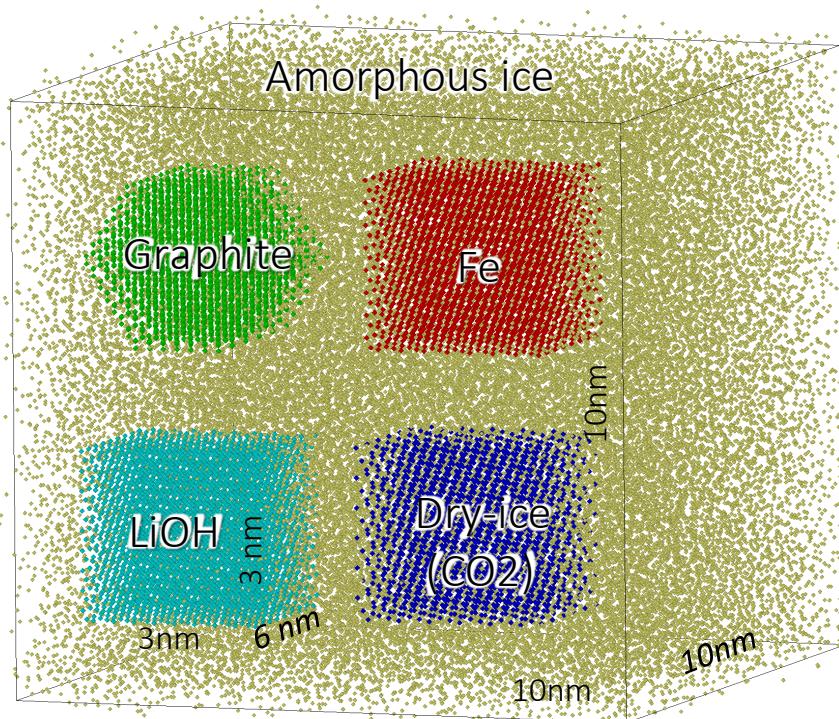
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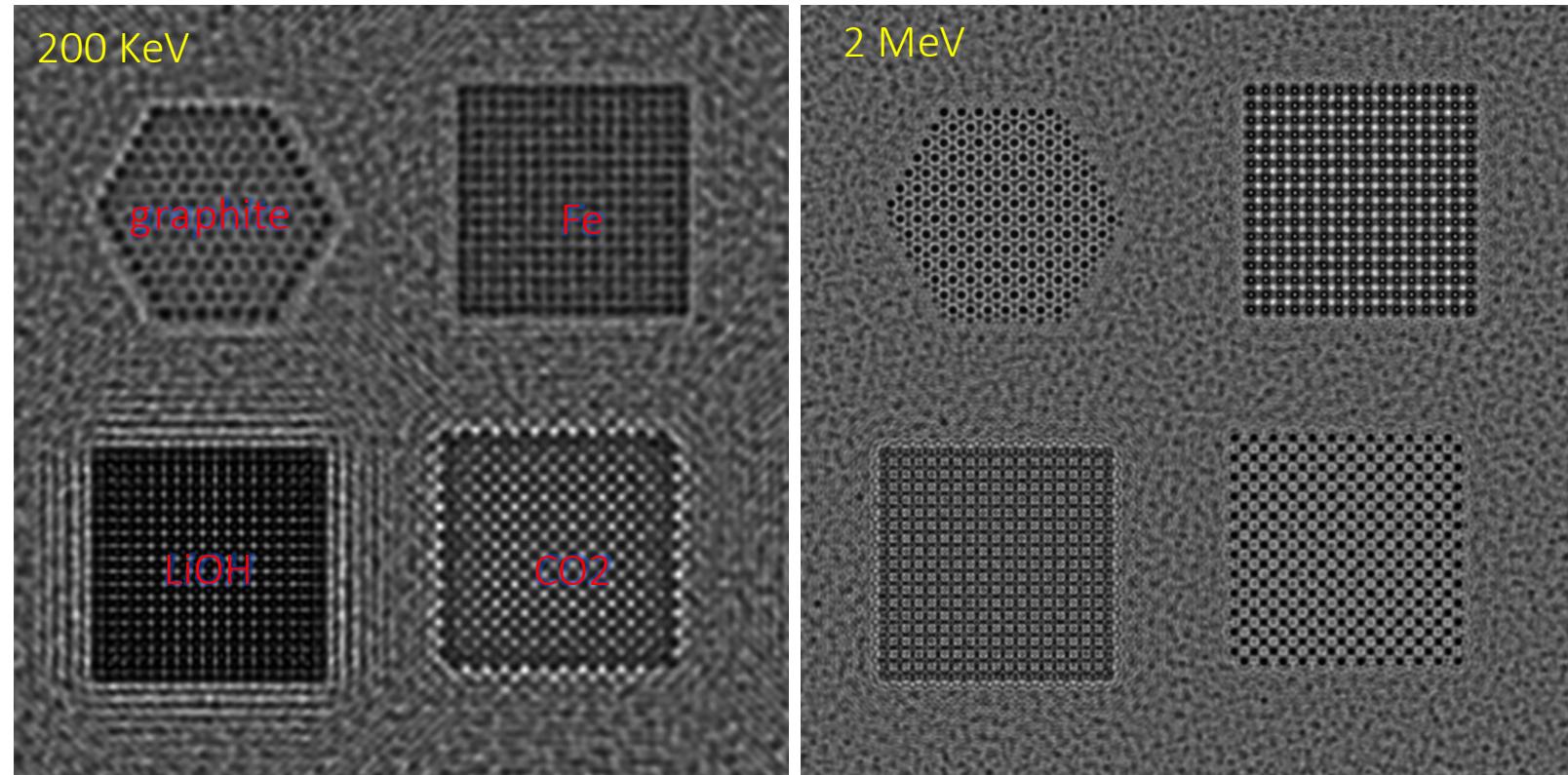
R.K. Li, et al., IBIC 2019

Benefit from increasing electron beam energy to mega-electron volt

Nanoparticle in amorphous ice

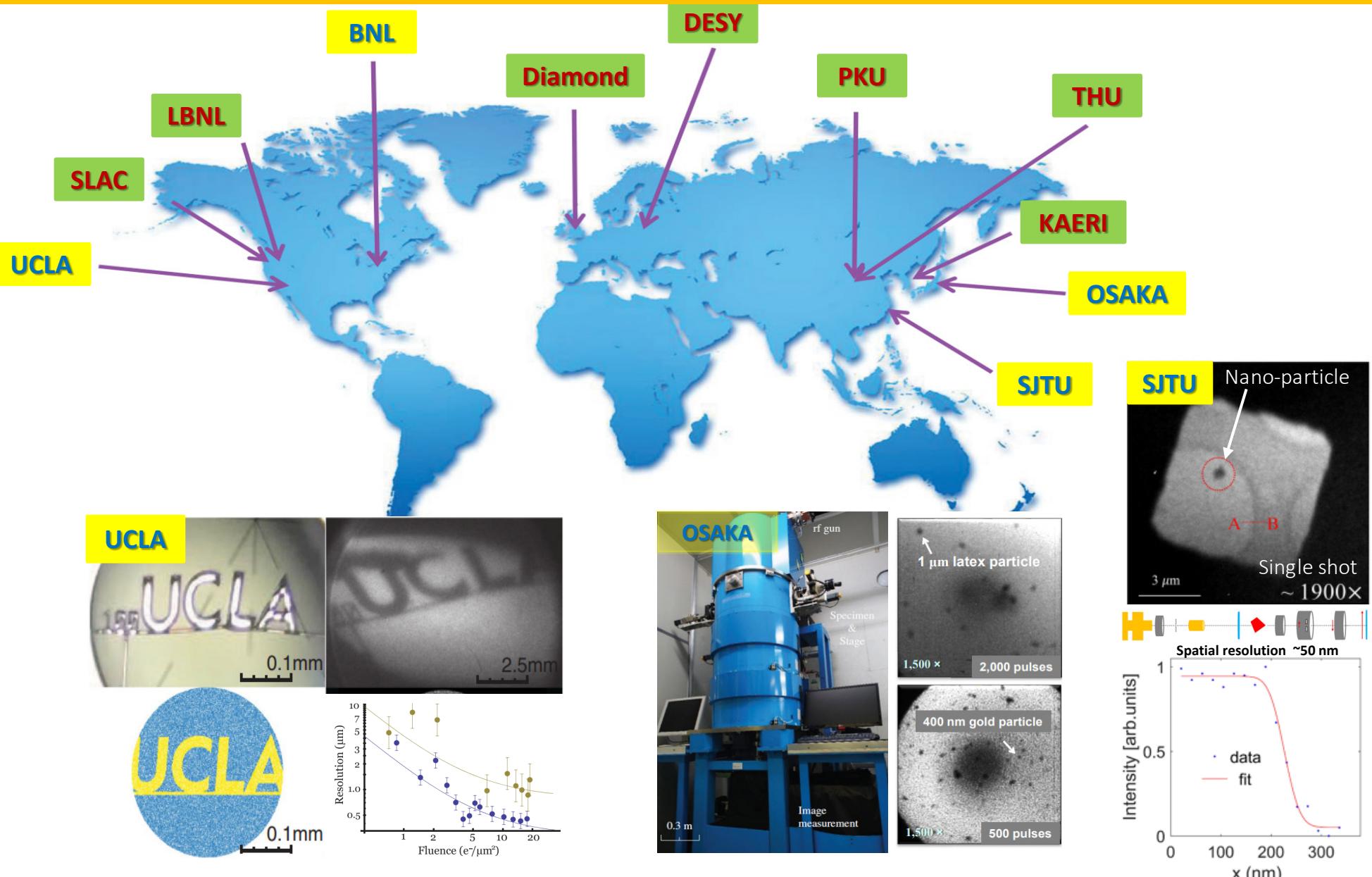
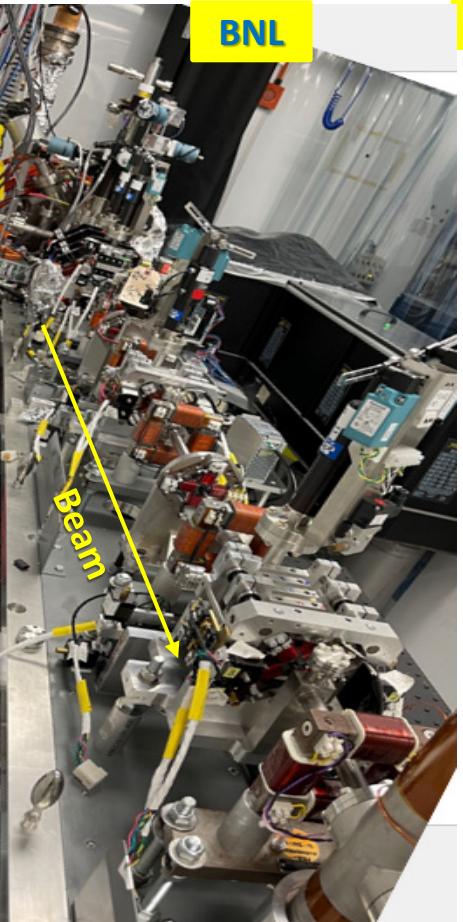


UEM Imaging at different beam energies



- Graphite, Fe, LiOH and Dry ice (CO_2) with size of ~ 3 nm in-plane and 6 nm thick are embedded in amorphous ice.
- The product of C_s and I is kept constant, we choose $C_s=0.5$ mm for 200 KeV and $C_s=2.5$ mm for 2 MeV.
 $D_0=5$ nm. Here $\Delta_0 = C_c \cdot \frac{\Delta E}{E}$.

State of art MeV UEM/UED: world-wide efforts



PRL 118, 154802 (2017)

Temporal resolution 180 fs

Microscopy 67, 291 (2018)

$$E = 3\text{MeV}, \frac{\Delta E}{E} = 5 \cdot 10^{-4}$$

Appl. Phys. Lett. 112, 113102 (2018)

Critical parameters and components for MeV UEM

- Beam requirement for single shot UEM

Number of electrons	10^7
Imaging area	$0.01 - 100 \mu\text{m}^2$
Beam divergence	$\leq 1 \text{ mrad}$
t - resolution	$10 \text{ fs to } 100 \text{ ps}$
Energy spread	$\sim 1 \times 10^{-5}$

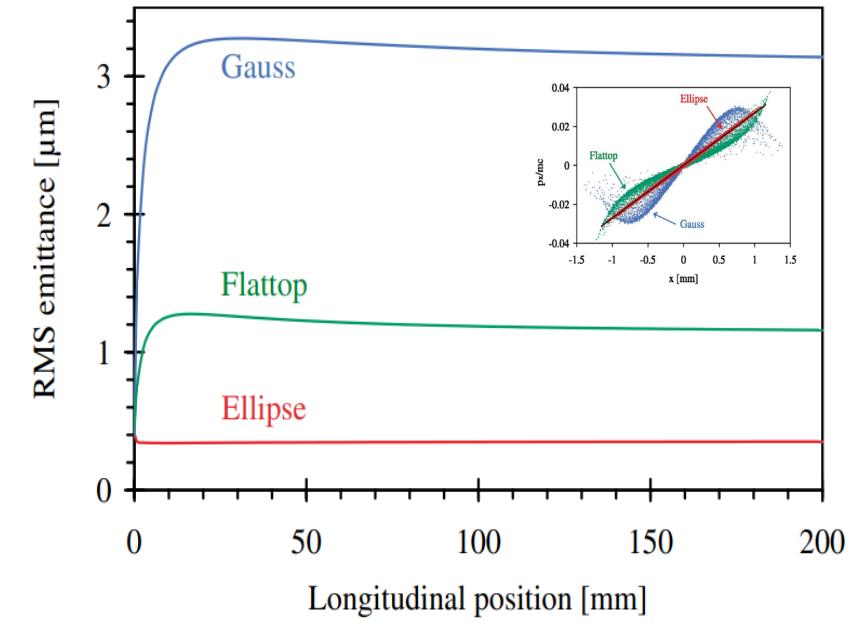
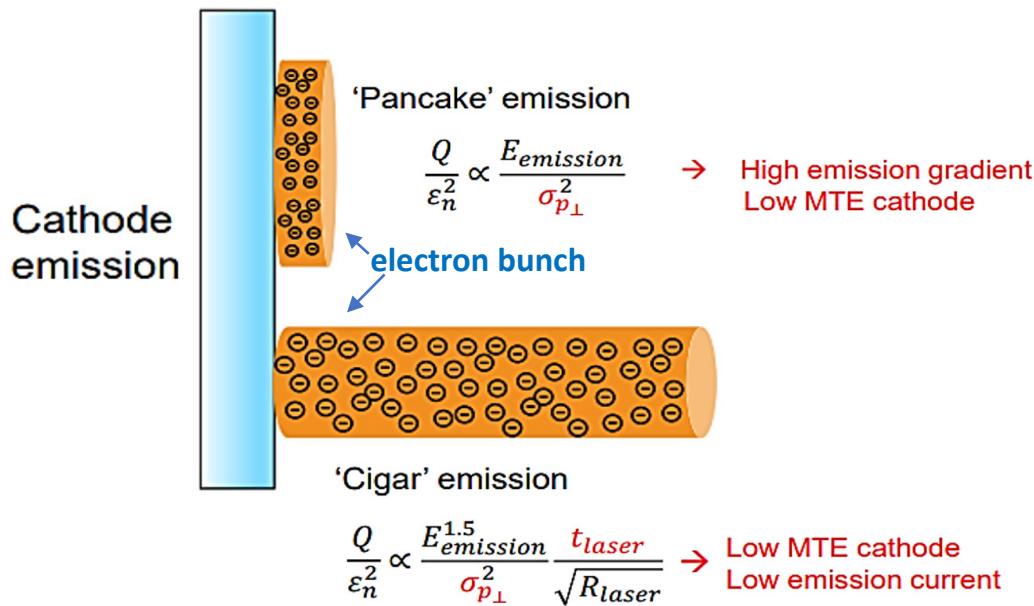
- < 10 nm emittance with > 1 pC
- Flattened longitudinal phase space for 1×10^{-5} energy spread

- Four main building blocks of MeV UEM

- High brightness photoinjector
Photocathode, high gradient rf gun, drive laser
- Bright beam transportation
Condenser, aperture, imaging lens system
- Electrons and sample interaction
Time-resolved applications, life science (e.g., bio-samples with up to 10 μm thickness)
- Detector
Scintillating, single electron counting (not for > 1MeV)

High brightness photoinjector

- Two types of photoinjectors
 - DC gun
 - RF gun (higher gradient)
 - Normal conducting
 - Superconducting
- Laser shaping affects tran. & long. dynamics
 - Uniformly filled ellipsoidal
 - Linear self-field



Emittance is preserved during beam transportation with an initial ellipsoidal profile

I. V. Bazarov et al., PRL **102**, 104801 (2009)

D. Filippetto et al., PRAB **17**, 024201 (2014)

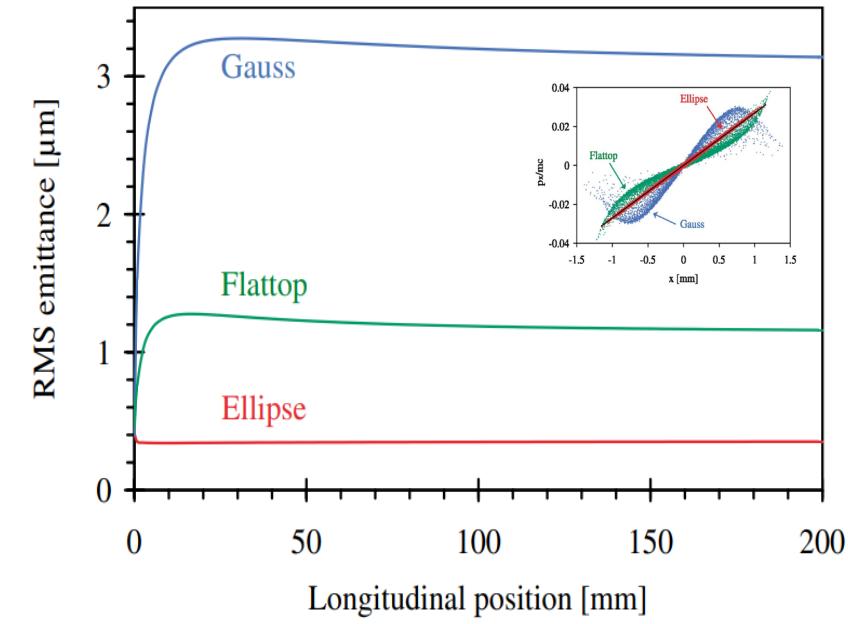
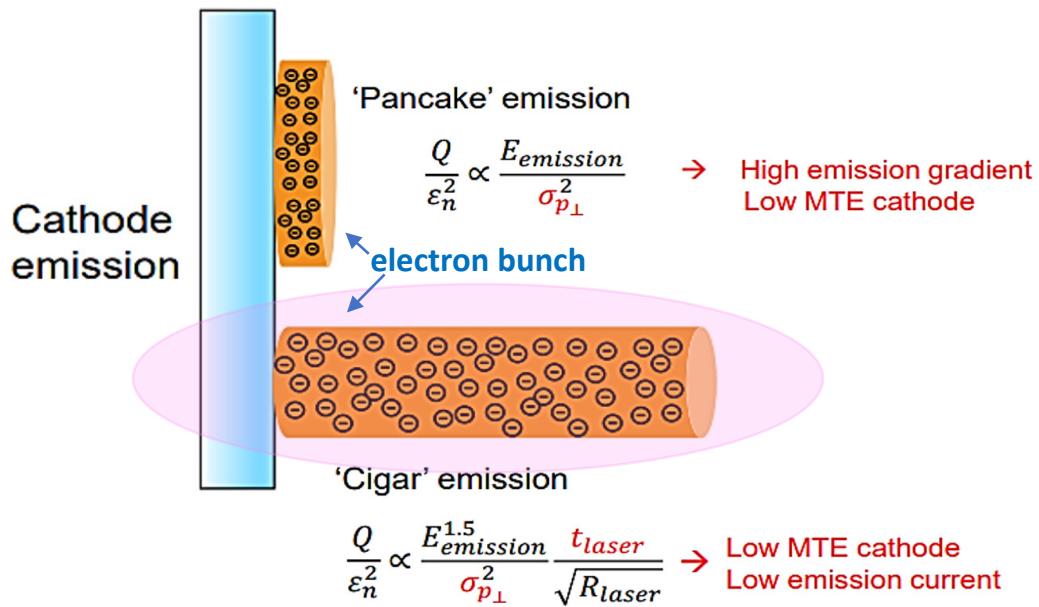
Qian and Vogel, IPAC21

O.J. Luiten, et al., Phys. Rev. Lett. **93**(9), 094802 (2004)

P. Musumeci et al., PRL **100**, 244801 (2008)

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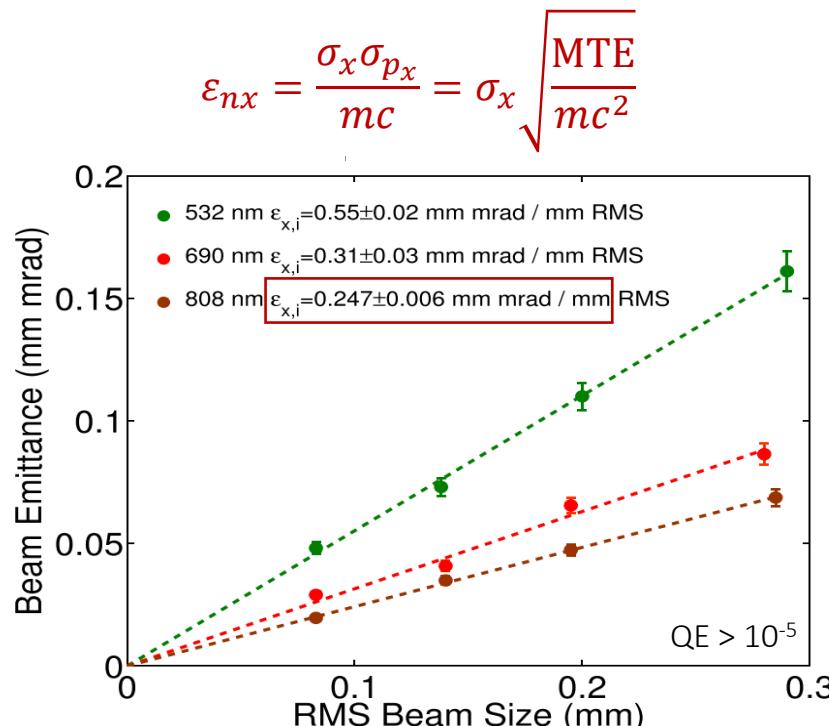
Challenges of MeV UEM

1. Reduce beam emittance to < 10 nm

$$\Delta r = C_s \alpha^3; \Delta r = C_c \alpha \Delta E/E; \varepsilon \propto \sigma_x \sigma_{x'}$$

- Reduce thermal emittance (minimize MTE & spot size)
- Reduce space charge induced emittance growth

Scherzer' theorem: $C_s < 0, C_c > 0$
(Scherzer, Z. Phys. **101**, 593 (1936))



Map to accelerator terminology

- Imaging requires: $R_{12} = 0$
- Chromatic aberration: $C_c = T_{126}$
- Spherical aberration: $C_s = U_{1222}$

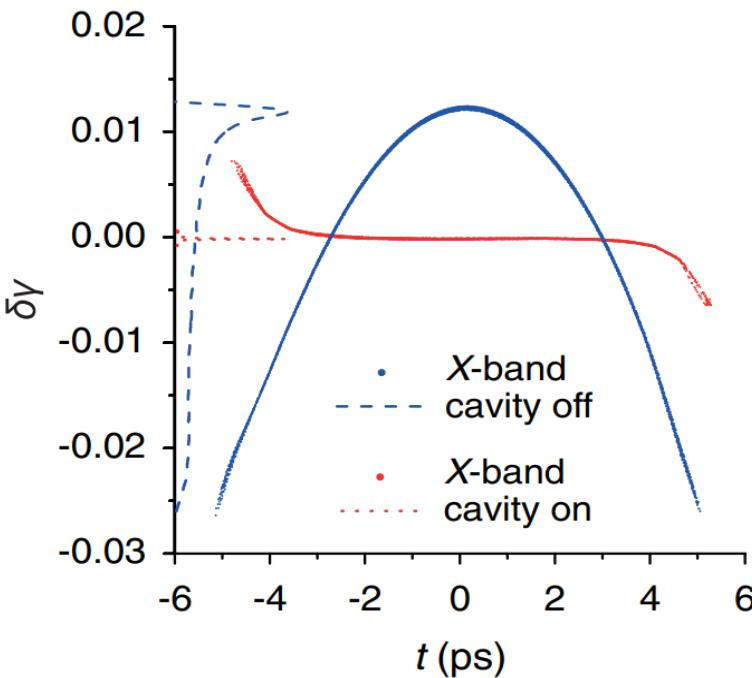
Assume rotational symmetry
Objective lens defines the aberrations

0.25 $\mu\text{m}/\text{mm}$ rms emittance is close to the limit set by e- finite $T=300 \text{ k}$
0.12 $\mu\text{m}/\text{mm}$ rms emittance when $T=90 \text{ k}$

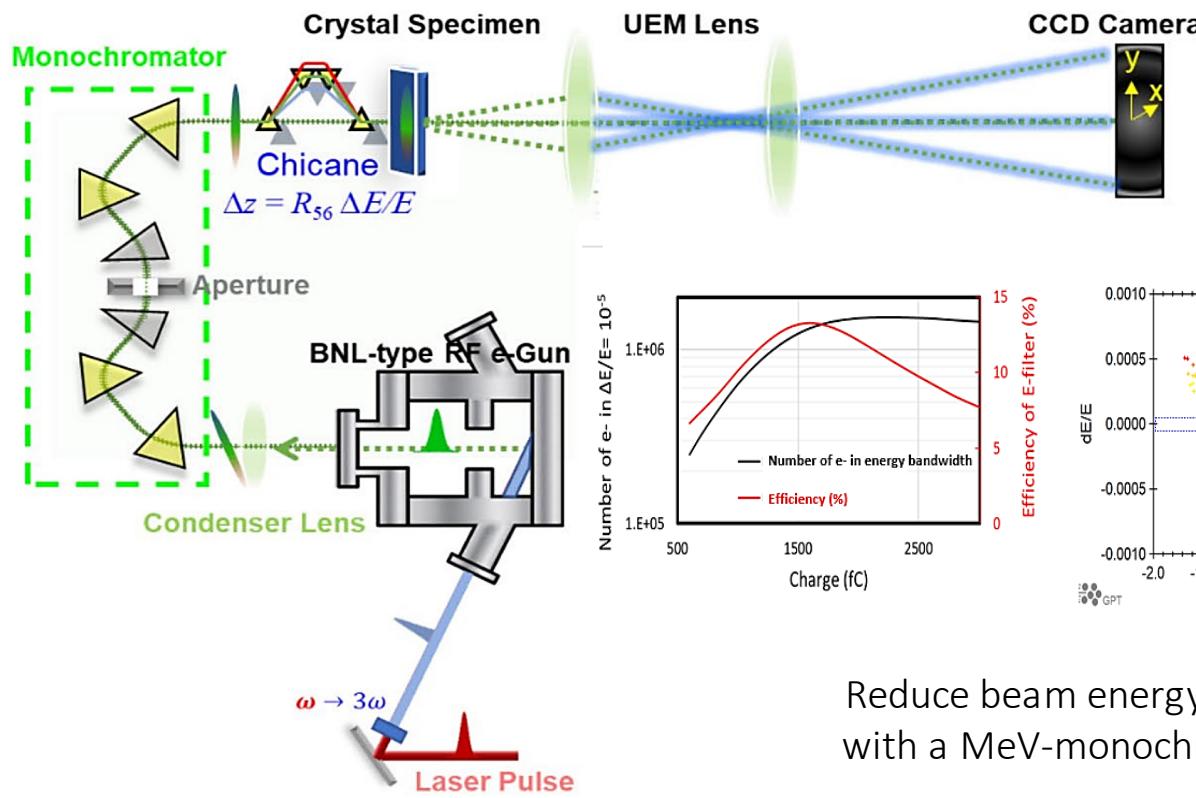
Challenges of MeV UEM

2. Reduce beam energy spread to $< 10^{-4}$

- Remove quadratic energy chirp with a harmonic cavity (single shot)
- Remove off-energy electrons with a monochromator (single- and multi- shot)
- Excellent RF and Low-level RF system



Reduce beam energy spread
with a harmonic cavity



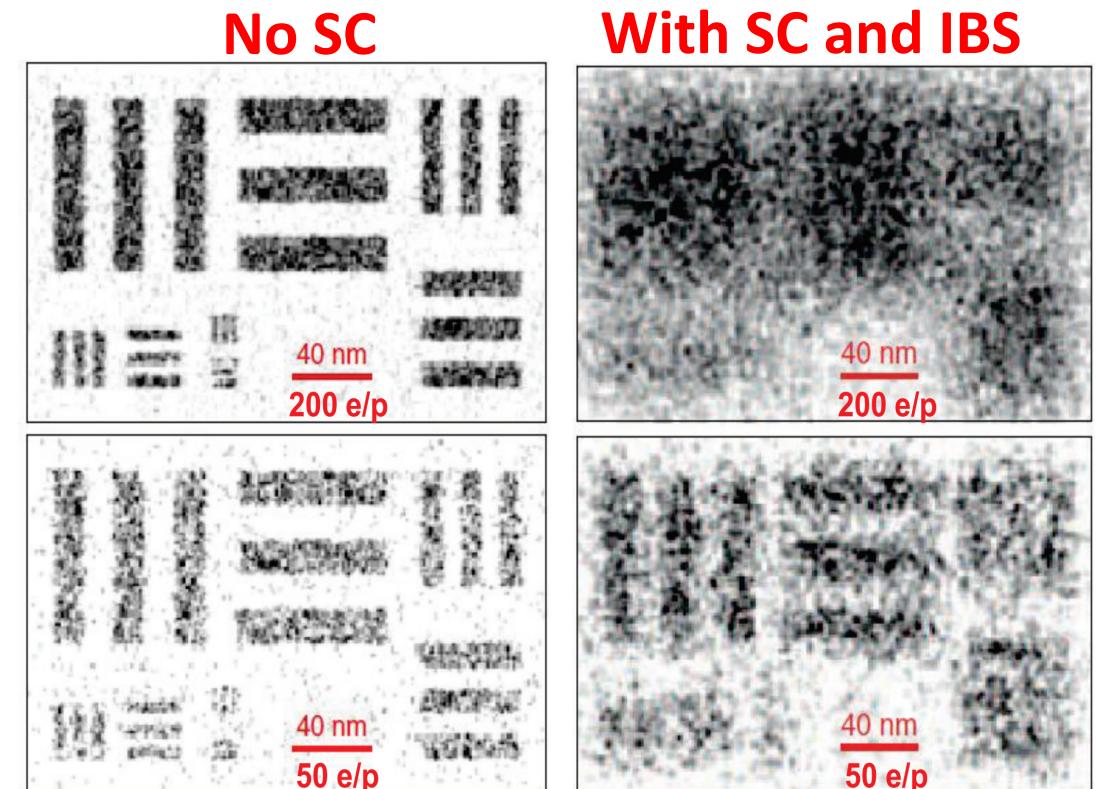
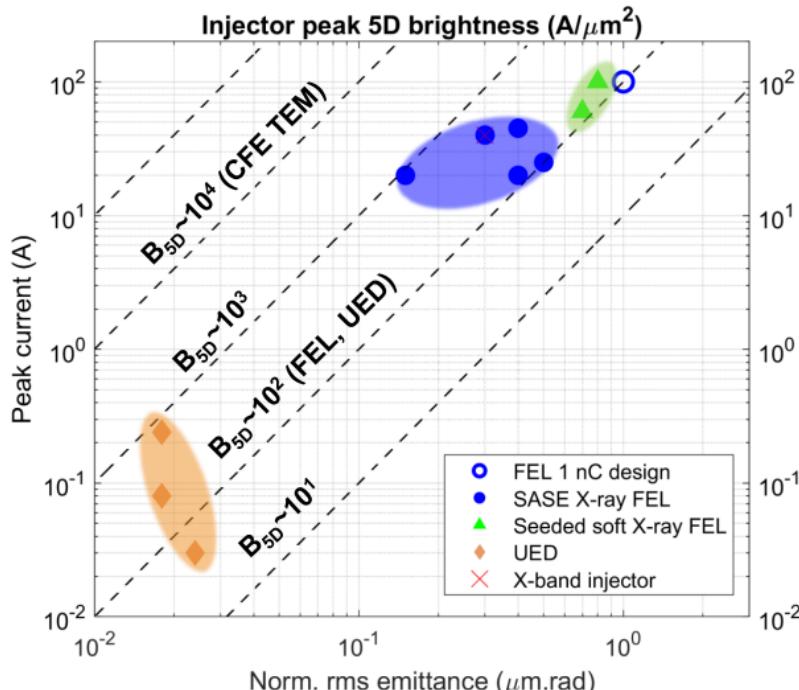
Reduce beam energy spread
with a MeV-monochromator

Challenges of MeV UEM

3. High beam density and space charge effect

- Rose theorem: >100 electrons/pixel to make a useful image
- Single shot UEM: $B_{6D} \frac{10^2-10^3}{\text{A}/(\text{keV}\cdot\mu\text{m}^2\cdot\text{rad}^2)}$
- Ultimate beam density ($\text{e-}/\text{nm}^3$) limited by space charge effect
- Spatial resolution also limited by stochastic space charge effect

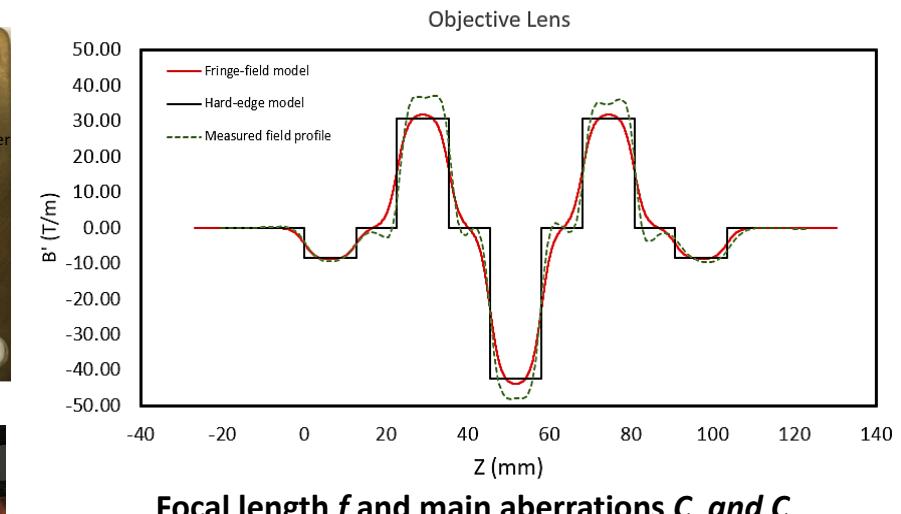
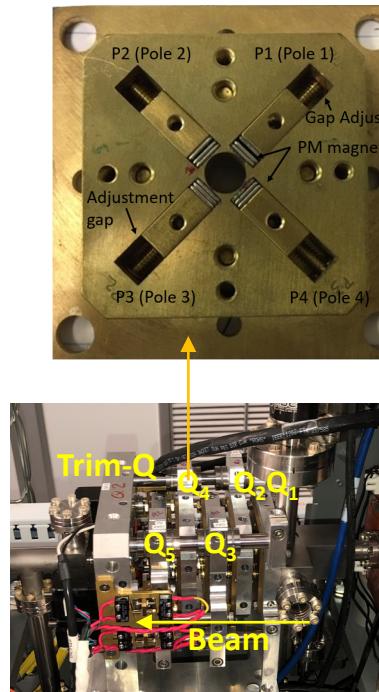
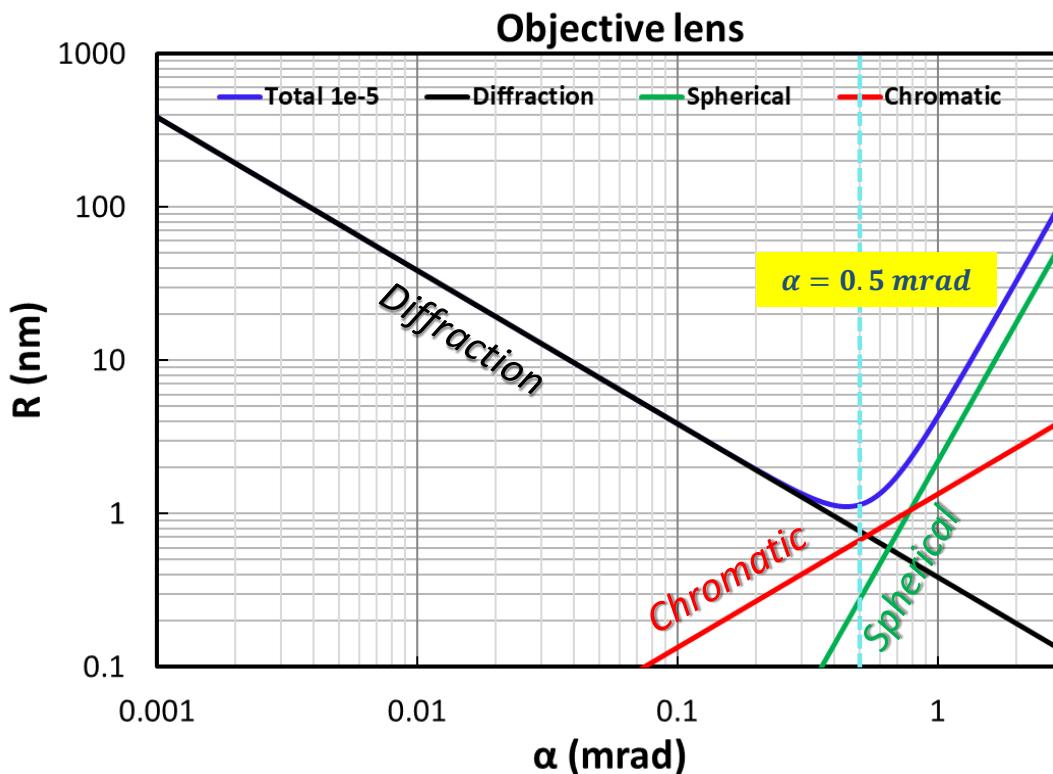
	Charge	Duration	ε_n (nm)	d_p/p
Diffraction	0.01-1 pC	0.1-1 ps	<100	<10 ⁻²
Single shot Imaging	>1 pC	10~100 ps	<10	<10⁻⁴



Challenges of MeV UEM

4. Build low-aberration strong lenses for MeV UEM at BNL

- Novel approach: compact low-cost imaging lens based on PMQ quintuplets.
- Minimum aberrations: strong lens with the highest achievable gradient and shortest focal length.
- Tunability of the magnification: +/- 5% by adjusting drift spaces between magnets and trim quadrupole.



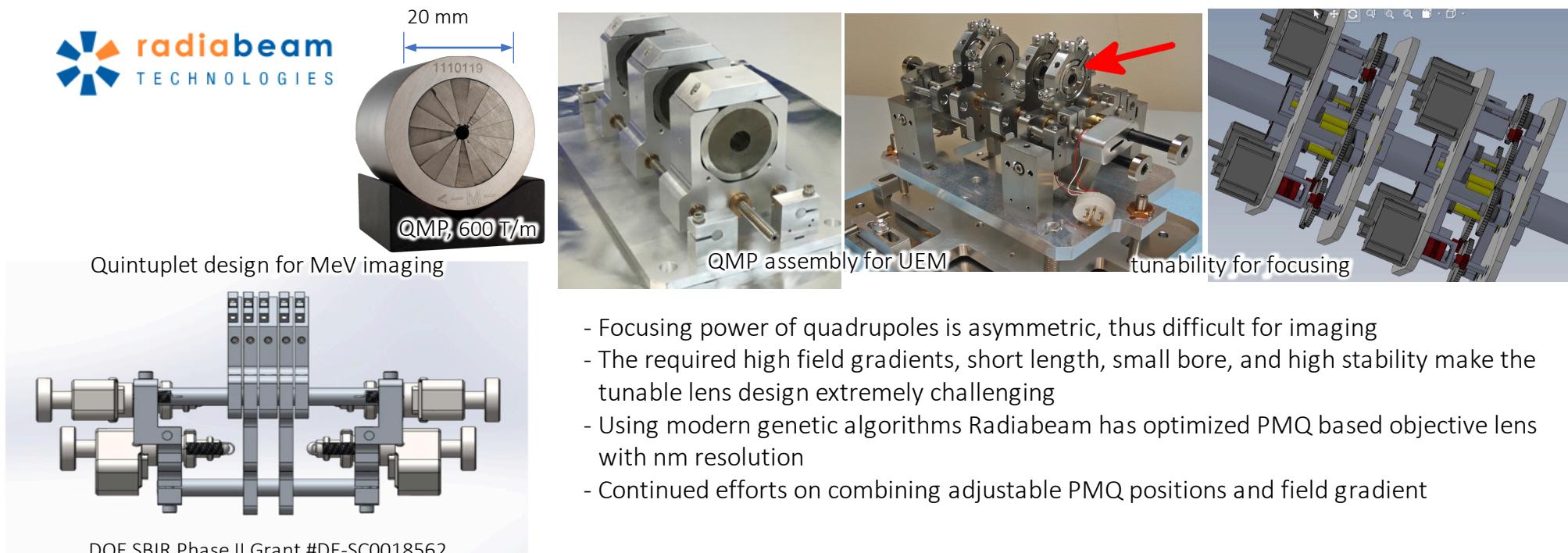
	f (cm)	$C_{s,x}$ (cm)	$C_{s,y}$ (cm)	$C_{s,xy}$ (cm)	$C_{c,x}$ (cm)	$C_{c,y}$ (cm)
Round lens	1.36	3.36	3.36	3.36	2.22	2.22
Quintuplet_BNL (measurement)	5.70	121	76.5	197	10.6	7.4
Quintuplet_BNL (analytical model)	6.20	215	106	336	13.4	9.7

Building a compact MeV UEM with small business

We are collaborating with small business to develop and construct a state-of-the-art MeV UEM. The collaborations are supported DOE SBIRs and the final products will be delivered to BNL for testing and optimization.

Quadrupole based focusing and imaging lens systems with Radiabeam

Quadrupoles are small, but have much stronger focusing capability for high energy electrons than round lens as their focusing power is inversely proportional to the momentum rather than momentum squared



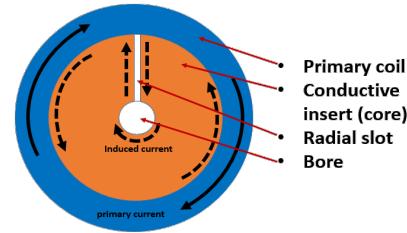
- Focusing power of quadrupoles is asymmetric, thus difficult for imaging
- The required high field gradients, short length, small bore, and high stability make the tunable lens design extremely challenging
- Using modern genetic algorithms Radiabeam has optimized PMQ based objective lens with nm resolution
- Continued efforts on combining adjustable PMQ positions and field gradient

Ultracompact Objective Lens for MeV UEM/UED*



Motivation:

- Reduce the weight and size of a bulky Tesla DC objective lens by 100 times using a flux concentrator based pulsed solenoid.



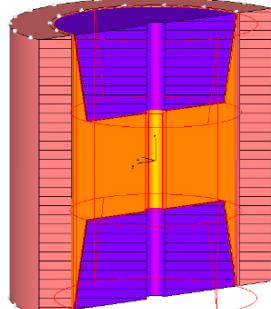
1Tesla DC solenoid with weight of 1Ton and 1m of overall diameter



2Tesla Flux Concentrator with weight of 1.5kg and 8cm of overall diameter



- Euclid 2T pulsed solenoid can achieve 2.3 Å resolution with $\frac{\Delta E}{E} = 10^{-5}$
- Limited repetition rate to a few Hz

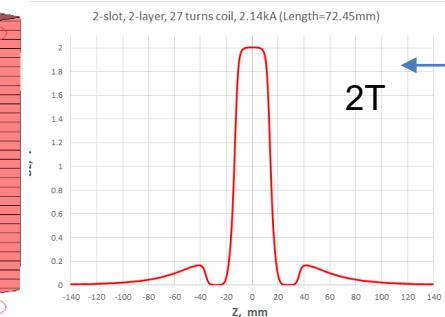


Orange – copper concentrator
Purple – ferrite insert
Red – water cooled coil

Euclid's Design:

- Using 2 slots to eliminate the dipole fields.
- Using ferrite to reduce the fringe fields
- Using high stability power supply and pulser to reach **10ppm** field stability.

Simulation



2T

Measurement@85%current

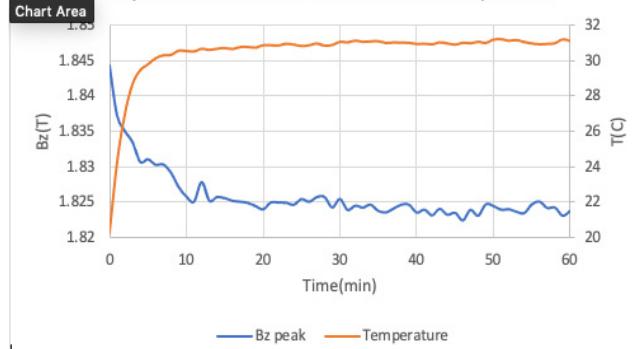


Position (mm)



Stability test over 1-hour

Polyscience chiller Bz and concentrator temperature



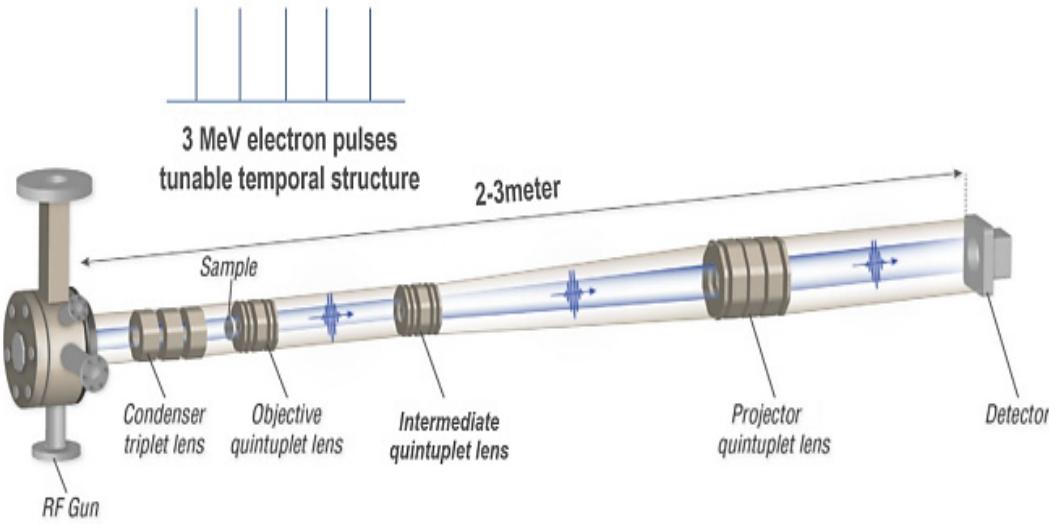
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Challenges of MeV UEM

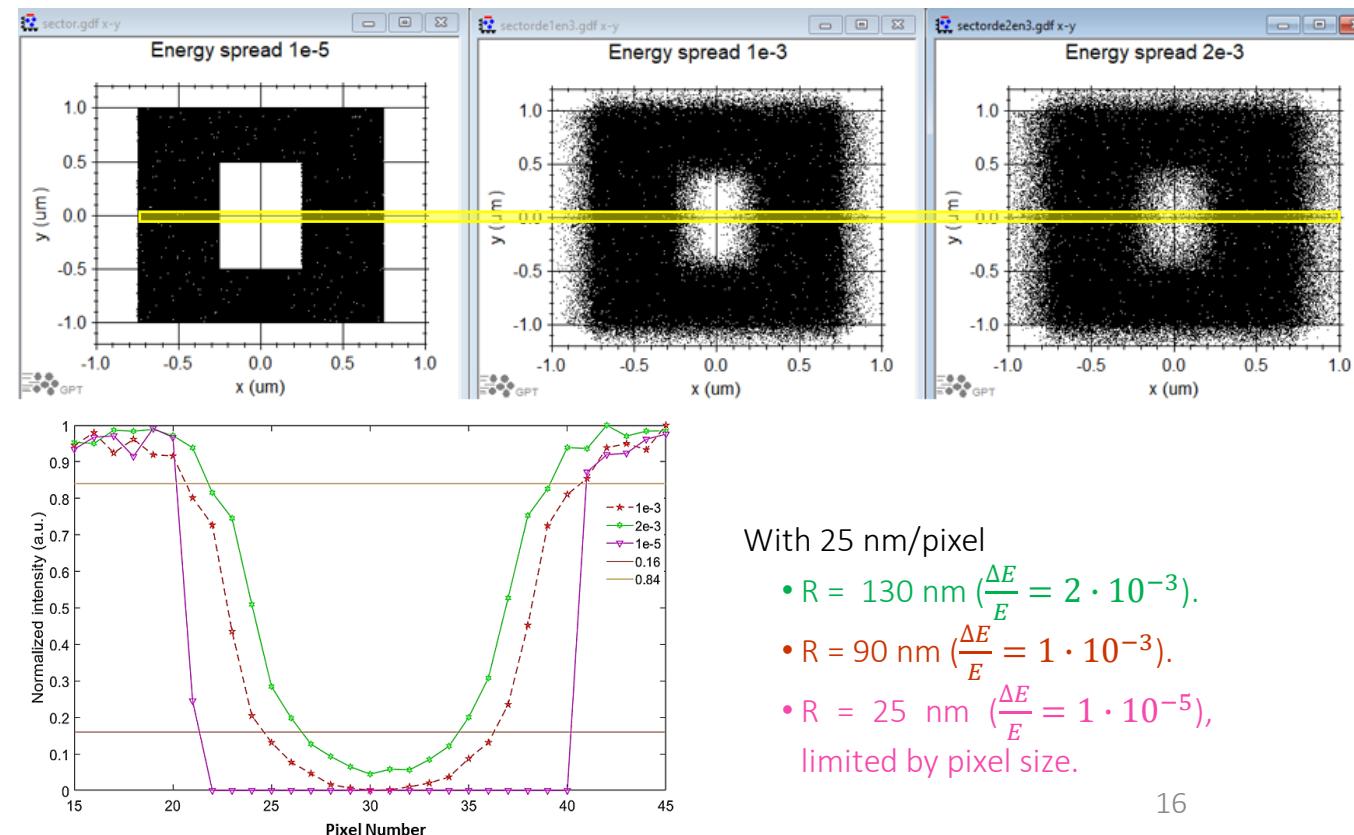
5. Design ultrafast microscope for single and multi-shot imaging with MeV electrons

- Modular design: future upgrade to higher magnification, towards atomic resolution.
- Real image at each stage: easy for commissioning.
- Simple design: make the objective and projector lenses identical.
- **The design resolution of** the lens system: **1.2 nm** with the low energy spread 10^{-5} and optimal aperture angle α 0.5 mrad.

Schematic of the UEM beamline

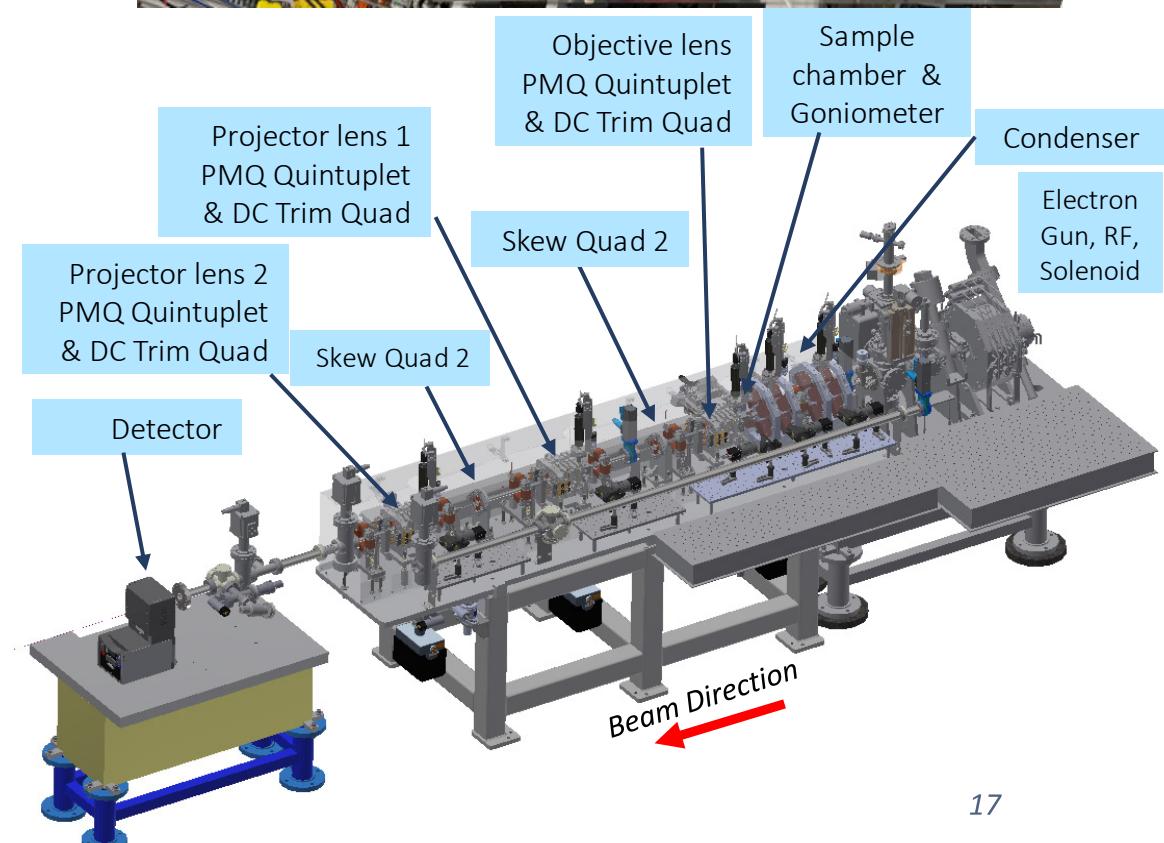
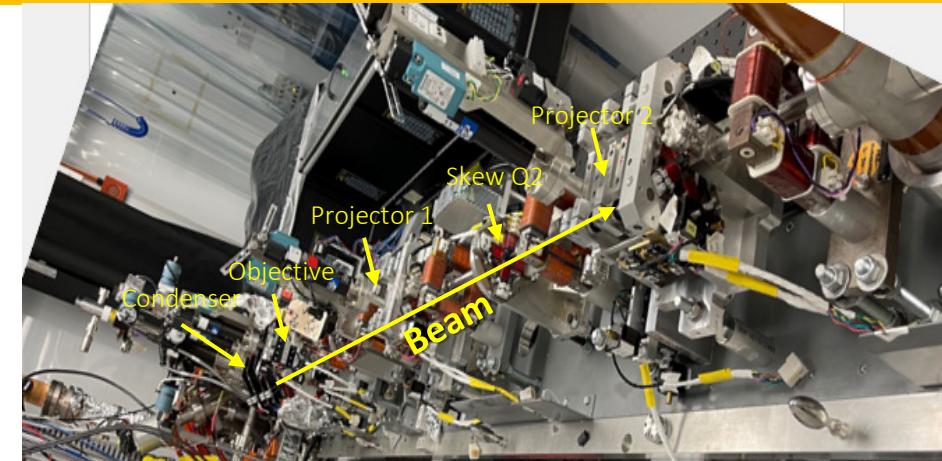


Start to end simulation



BNL efforts: construction of tunable quadrupole-based UEM

- A MeV UEM: simultaneous high spatial and high temporal resolution for probing ultra-fast and small world
- Constructed the world first compact 3 MeV quadrupole-multiplets UEM system based on
 - Our conceptual design (*Wan, Chen & Zhu, 194 Ultramicroscopy, 143-153, 2018*)
 - Success of UED LRD
- The UEM consists of tunable condenser-, objective- and projector-lenses and various steering magnets.
- A modular design allows the future upgrade from 2000X to 100,000X Using the high spatial resolution compact lens system constructed by Radiabeam and/or Euclid supported by DOE SBIRs.
- Design resolution of 1.2 nm lens can be achieved with $\Delta E/E = 10^{-5}$.
- Preliminarily designed a monochromator with energy acceptance of 10^{-5} .



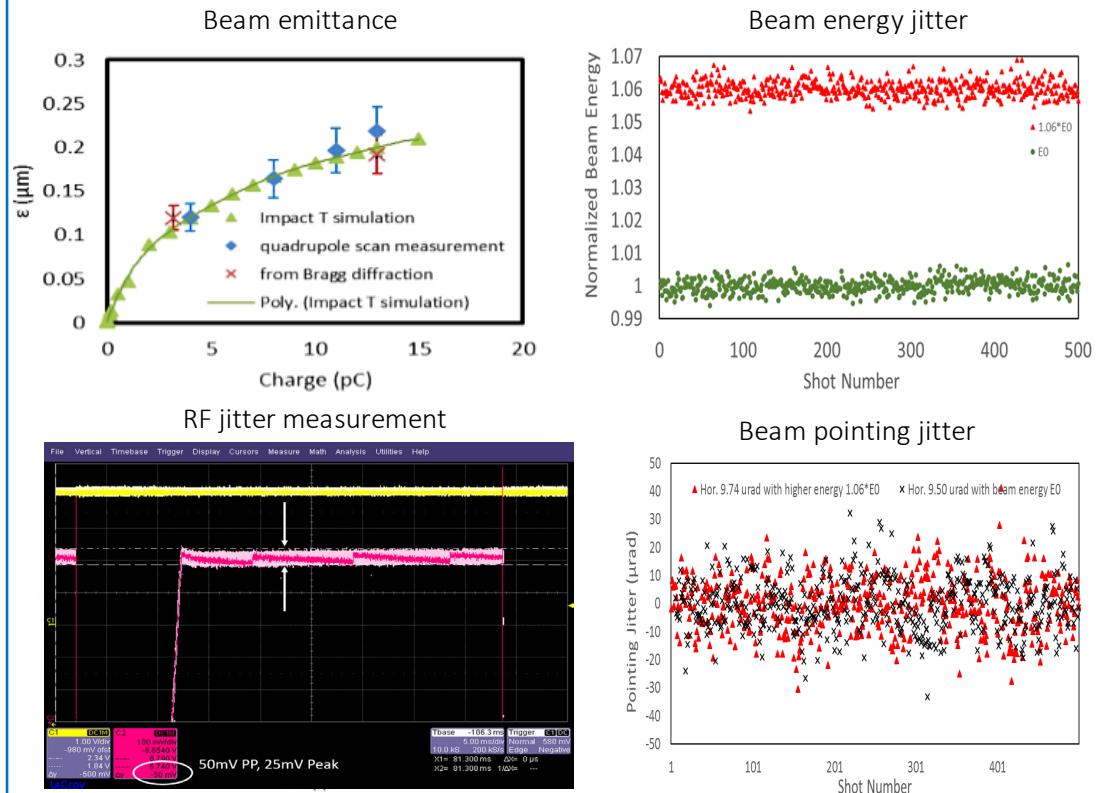
Beam Stability Requirement for nanometer UEM

Energy and spatial-pointing stability requirement

- The RF system is the dominant source of shot-to-shot pulse jitter
- We use two methods for the energy jitter measurement:
 - Bragg Diffraction Method
 - Direct RF jitter measurement
- Nanometer resolution needs RF stability in the level of 10^{-5}
- Future improvement of RF system toward nm resolution
 - HVPS (ScandiNova SS-K300@30ppm)
 - RF harmonic cavity
- Implement monochromator with $1 \cdot 10^{-5}$ energy acceptance
- Stable source + narrow-band optics can achieve nm resolution in either single-shot or multi-shot mode.
- Shot-to-shot spatial pointing jitter is $\sim 10 \mu\text{rad}$

Development of real time, nondestructive diagnostic methods for MeV electron pulses

BDM allows us to optimize beam quality including the beam emittance, energy spread, shot-to-shot pulse fluctuation and jitter in real time.



Mechanical Tolerances for nanometer UEM

- Magnet tolerances:
 - Manufacture and measurement tolerances
 - Alignment tolerances
- The lens system with 5% tunability requires
 - Manufacture tolerance of the gradient error $\Delta B' / B' = \pm 2\%$
 - Measurement tolerance (Table)
- Alignment tolerance is determined by sample plane defocus: $\Delta D = \alpha \cdot R_{12} / R_{11} \leq \text{Resolution}$.
- UEM system dimension scales with magnet gradient (for round lens)
 - $1/f = \frac{eGL}{p}$. Short focal length needs high gradient (HG)
 - UEM LDRD builds experience with low gradient (LG) (up to 44 T/m) $f (= 6.2 \text{ cm})$
 - Total beamline $L = 4.2 \text{ m}$
- Toward nm UEM with a compact beamline design.
 - Two SBIRs for high gradient short focal length objective lenses.
 - Stability prefers compact system

$$M^1 = \begin{pmatrix} R_{11} & R_{12} \\ R_{21} & R_{22} \end{pmatrix}$$

magnification → angle-to-position spread →

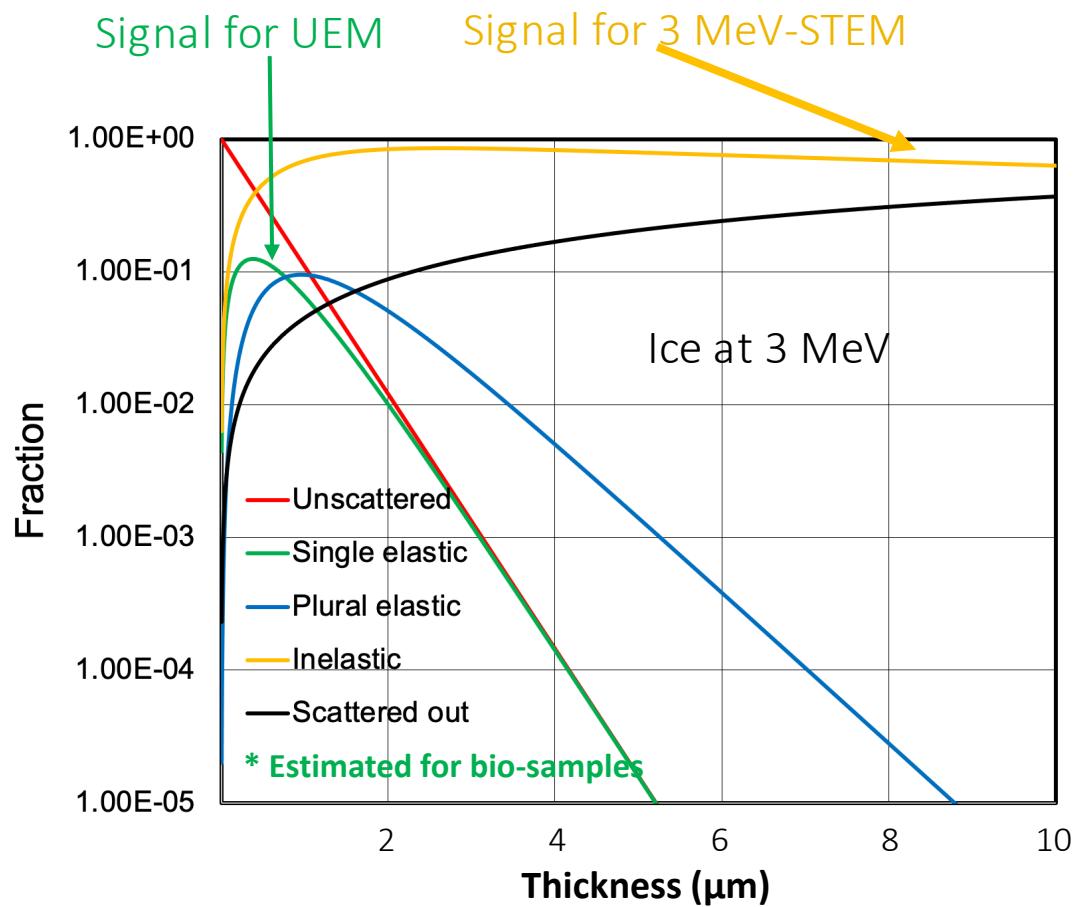
Alignment	Q1	Q2	Q3	Q4	Q5
Roll (mrad)	13	2.8	1.1	1.5	3.5
Pitch-x (mrad)	10.5	5	2.8	4	6.6
Yaw-y (mrad)	10.5	4.3	4.3	3.5	6.7
$\Delta x (\mu\text{m})$	11	6	6	9	40
$\Delta y (\mu\text{m})$	13	4	5	11	40
$\Delta z (\mu\text{m})$	56	5	5.6	6.6	36
Manufacture $\Delta B'/B' (\%)$	± 2	± 2	± 2	± 2	
Measured $\Delta B'/B' (\%)$	± 1.4	± 0.5	± 0.2	± 0.5	± 1.5

** Q1, Q2, Q3, Q4 and Q5 are quadrupole #1, 2, 3, 4 and 5 in a UEM lens assembly

MEV STEM to visualize intact cells

Understand cell biology and microbiology in cellular context
(imaging of intact plant and bacteria cells)

- Beam size and converging angle on sample determines resolution.
- To achieve 2-10 nm with up to 10 μm sample thickness:
 - (1) Electron dose: 200 $e^-/\text{nm}^2 / \mu\text{s}$
 - (2) Probe on sample: 1-5 nm
 - (3) Beam convergence angle: 1 mrad
 - (4) Beam flux: 200 - 5,000 $e^-/\mu\text{s}$
 - (5) Scanning accuracy: 1 nm

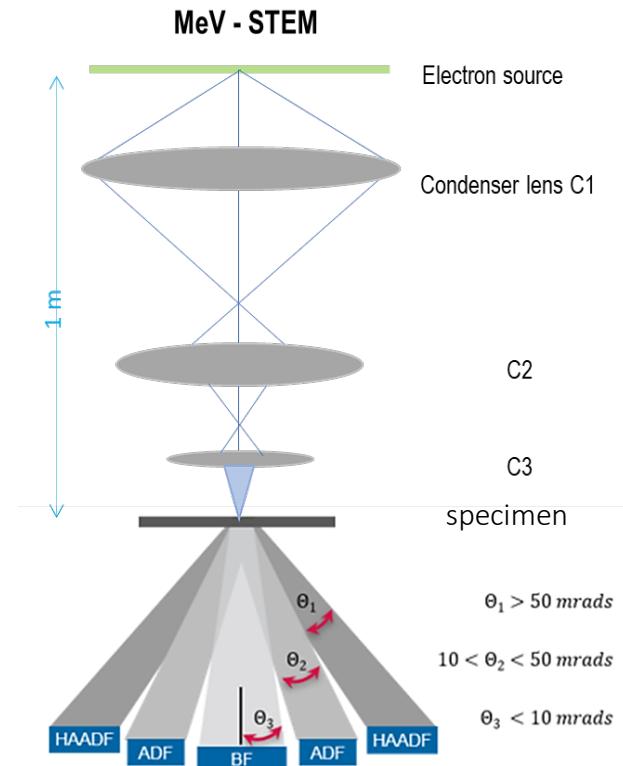
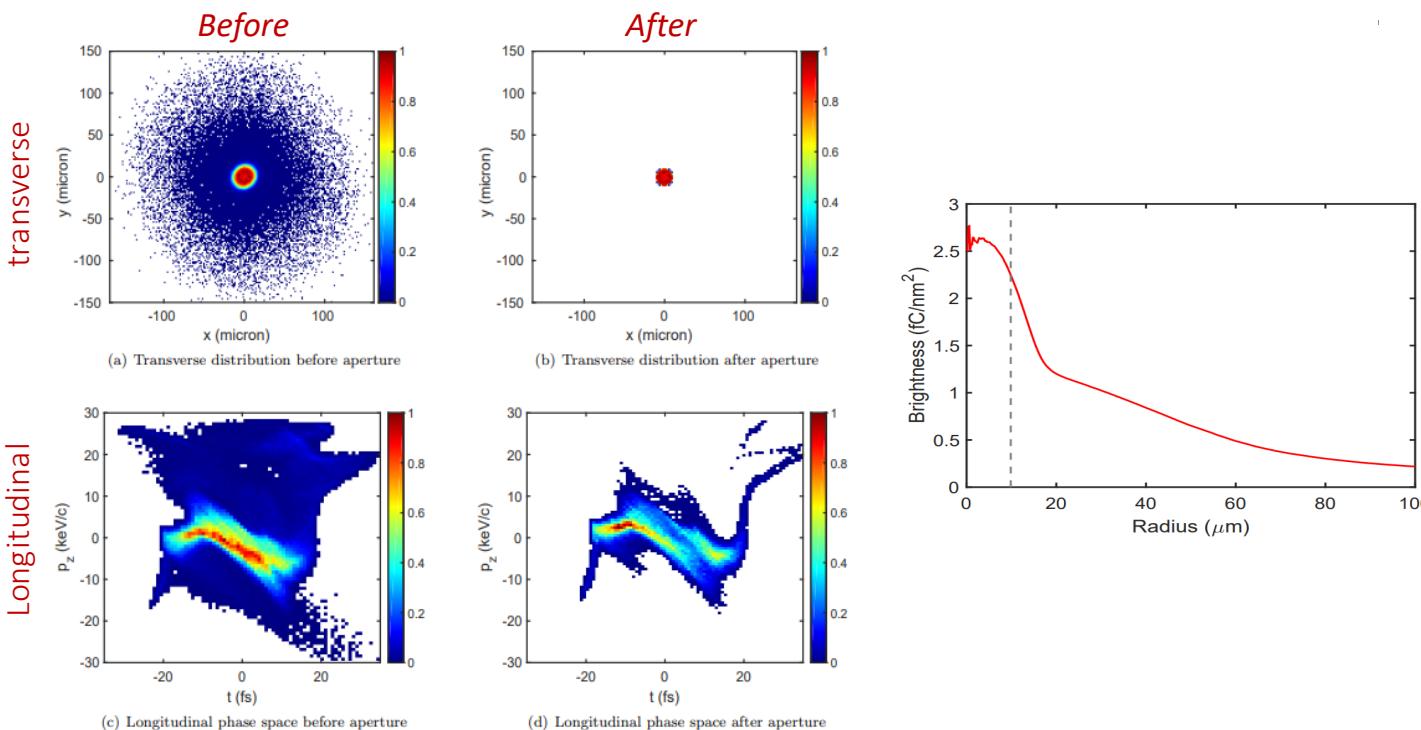


Challenges of MeV STEM

1. Reduce beam emittance to $\sim 2 \text{ pm}$ with current of $30 - 750 \text{ pA}$
2. Photocathodes & beam dynamics to improve brightness by >1000

Probe size: $\sigma_r = 2 \text{ nm}$; divergence: $\sigma_{r'} \leq 1 \text{ mrad}$; emittance: $\varepsilon \leq 2 \text{ pm}$

- Reduce laser spot size and MTE from photocathode $\rightarrow \varepsilon \approx 2 \text{ pm} \cdot \text{rad}$
- Increase QE $\geq 10^{-5}$
- Beam dynamics come hand in hand with improved emittance
 - Apply aperture to increase both transverse and longitudinal brightness
- Preliminarily MeV-STEM design (reversal of UEM to cathode to sample)
- Assume 20 μm spot at cathode
- Dose rate 200 to 5k e-/ μs

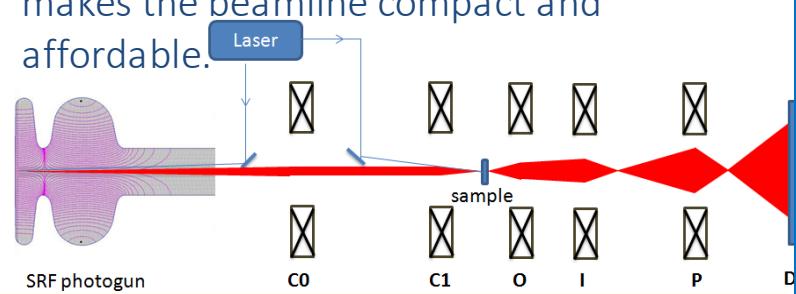


A promising source for UEM/STEM and UED: SRF photogun

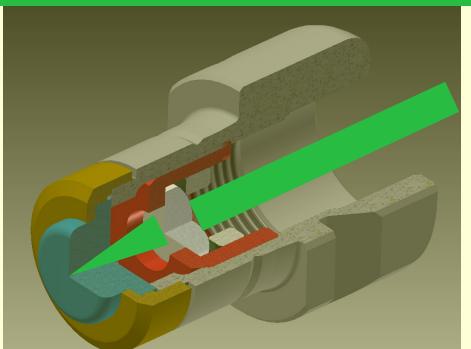


Introduction:

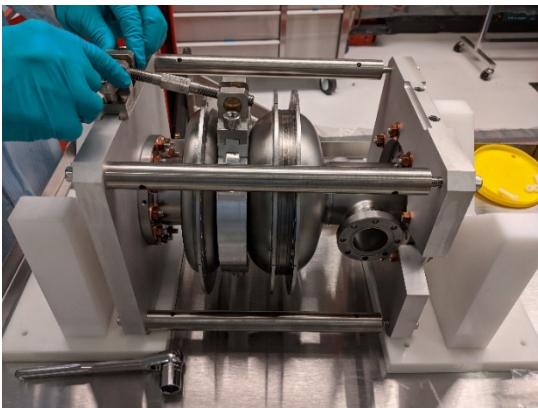
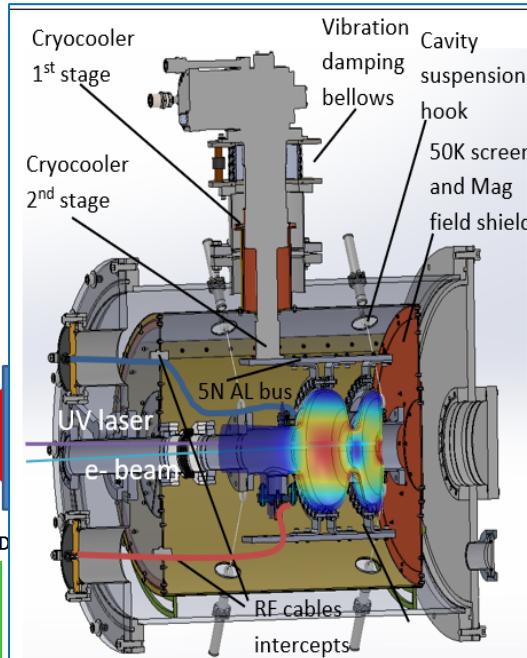
- Aimed for the first CW MeV UEM/UED application with RF frequency **1.3 GHz**.
- Using **conduction cooled Nb₃Sn** SRF photogun. Only 2W of RF power and one cryocooler are required, which makes the beamline compact and affordable.



Low- ϵ (alkali antimonides) photocathodes in high field RF guns were operated with 100s of hours at CERN. A UCLA variant of INFN/DESY cathode plug allows μm spot size in transmission mode with a short f lens.



H. Lee et al., Rev. Sci. Instrum. **86** (2015) 073309



Current Status:

- The cryomodule was commissioned: cooled down to 2.5K; magnetic field at room temperature is below 5mG.
- SRF gun (pure Nb) was tested at 2K resulted in $Q_0=10^{10}$ and reached $E_z=47\text{MV/m}$ on axis field.
- 1st Nb₃Sn test was conducted but low $Q_0=4\cdot10^9$ at 4K (the film was damaged during the gun assembly)
- 2nd Nb₃Sn coating has been applied; test is coming.



Parameter	Value	
Application	UED	UEM
Beam energy	1.7MeV	1.7MeV
Charge	5fC	0.5pC
Energy spread (relative)	1.3e-5	6.4e-5

Details refer to a talk by Roman Kostin in this conference.

Summary

- Accelerator based MeV UEM/STEM hold great potential for solving the challenges in probing matter at ultrafast temporal and ultrasmall spatial scales and studying life science
- Expected better performance than low-energy UED/UEM for thick samples
- Several MeV UED user facilities are being built and deliver high impact results
- MeV UEM efforts are ramping up
- MeV STEM is just in the beginning
- A great complement to XFELs
- Inter-discipline collaboration generates creative idea: real-time nondestructive Bragg diffraction based diagnostic methods

BNL UED/UEM Team

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Thank you!